

In-situ optical testing of exposure tools via localized wavefront curvature sensing

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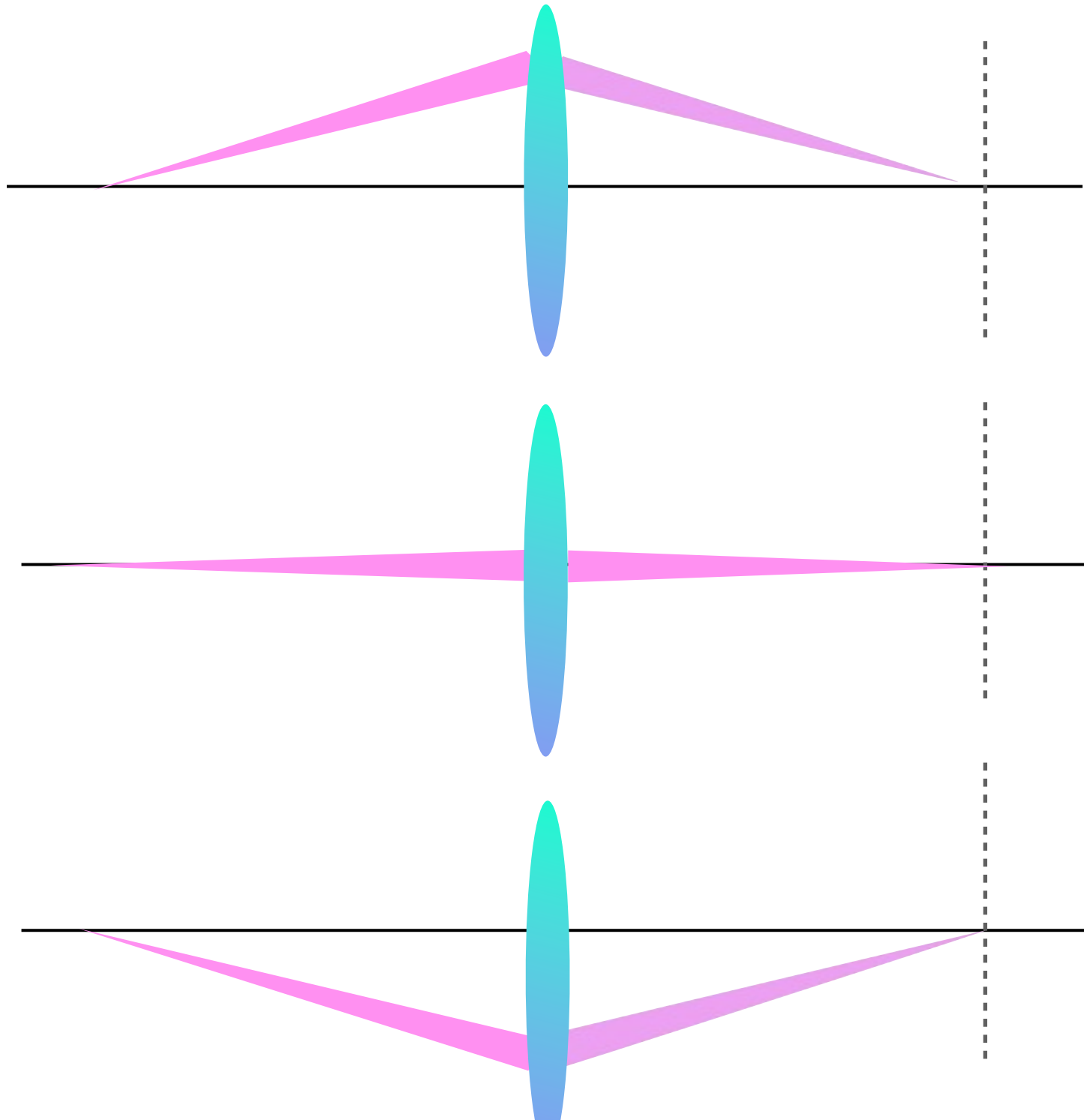


A new optical test

1. In-situ
2. Non-interferometric
3. Simple integration
4. Scales to high NA (and smaller λ)

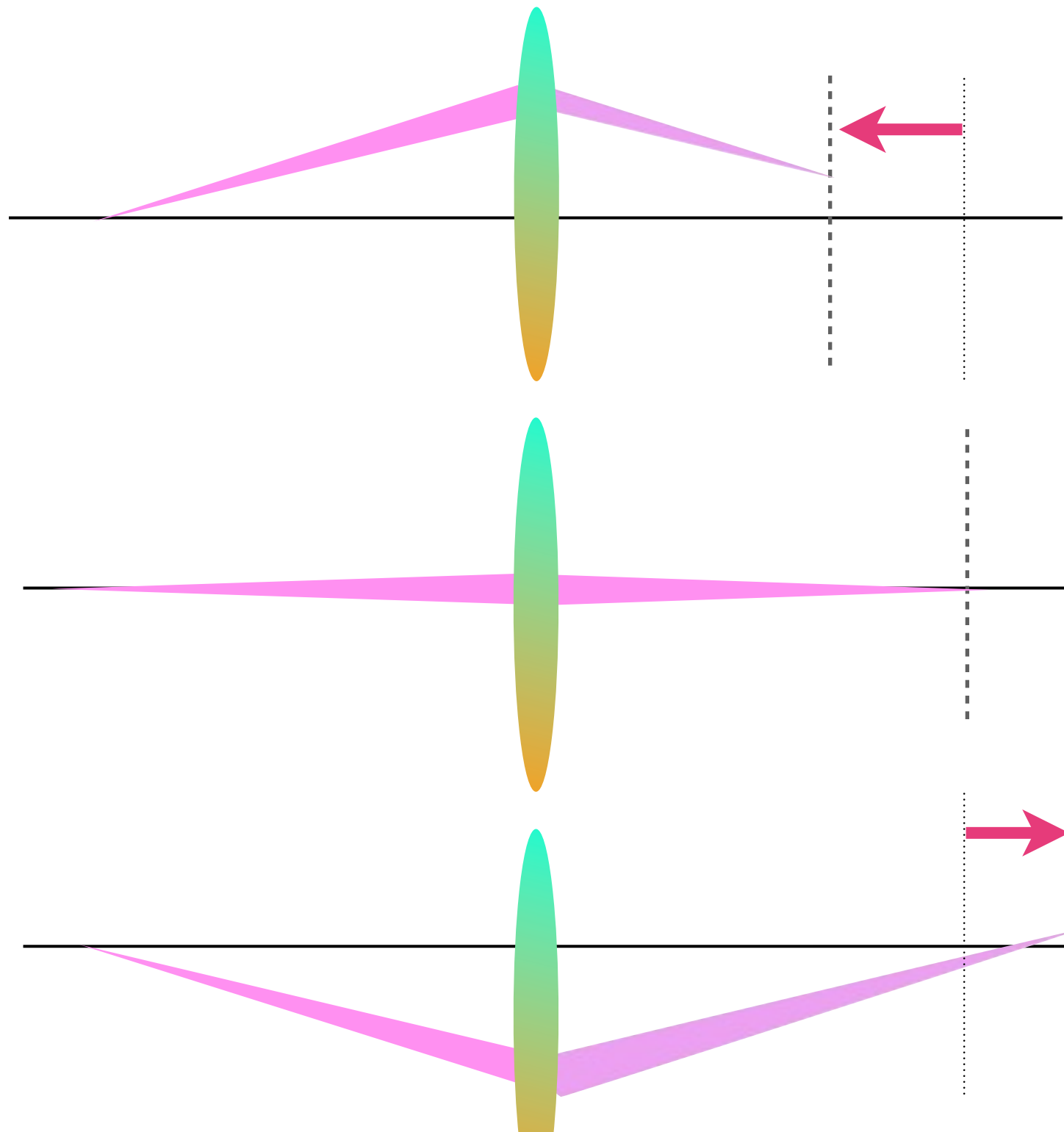
Basic idea: Aberrated optical systems have nonuniform focus signatures over pupil

No aberrations

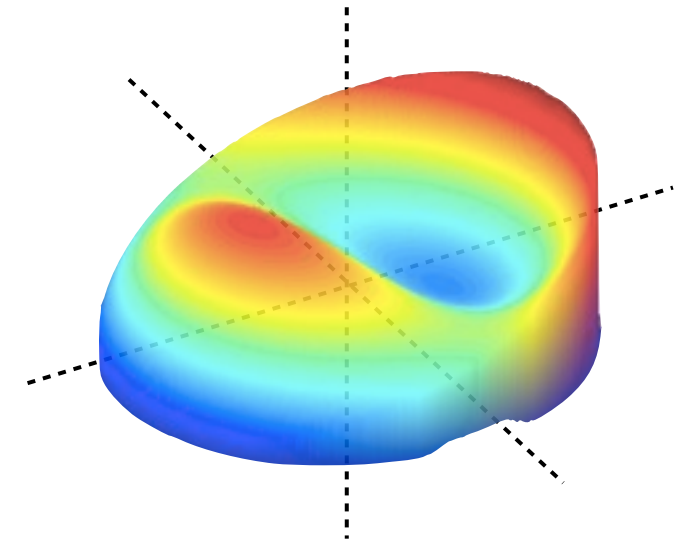
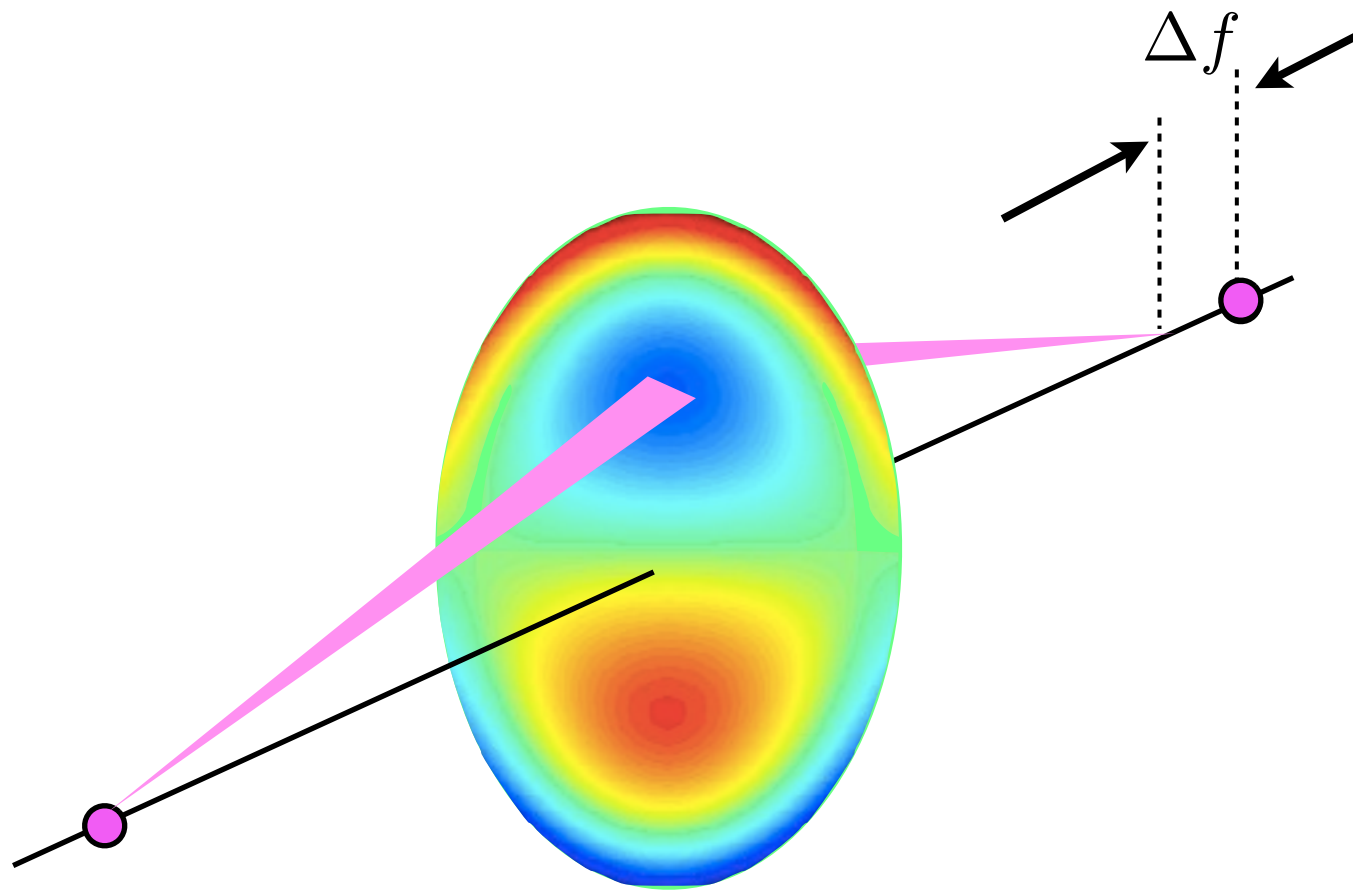


Basic idea: Aberrated optical systems have nonuniform focus signatures over pupil

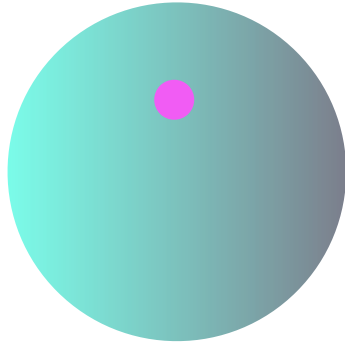

Aberrated



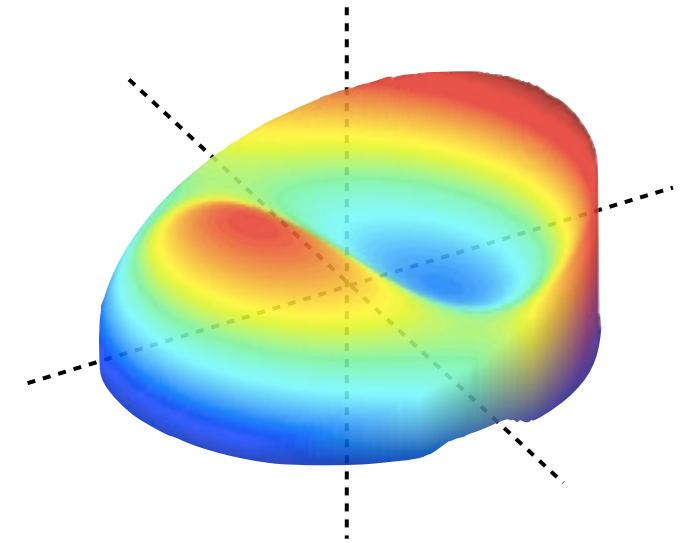
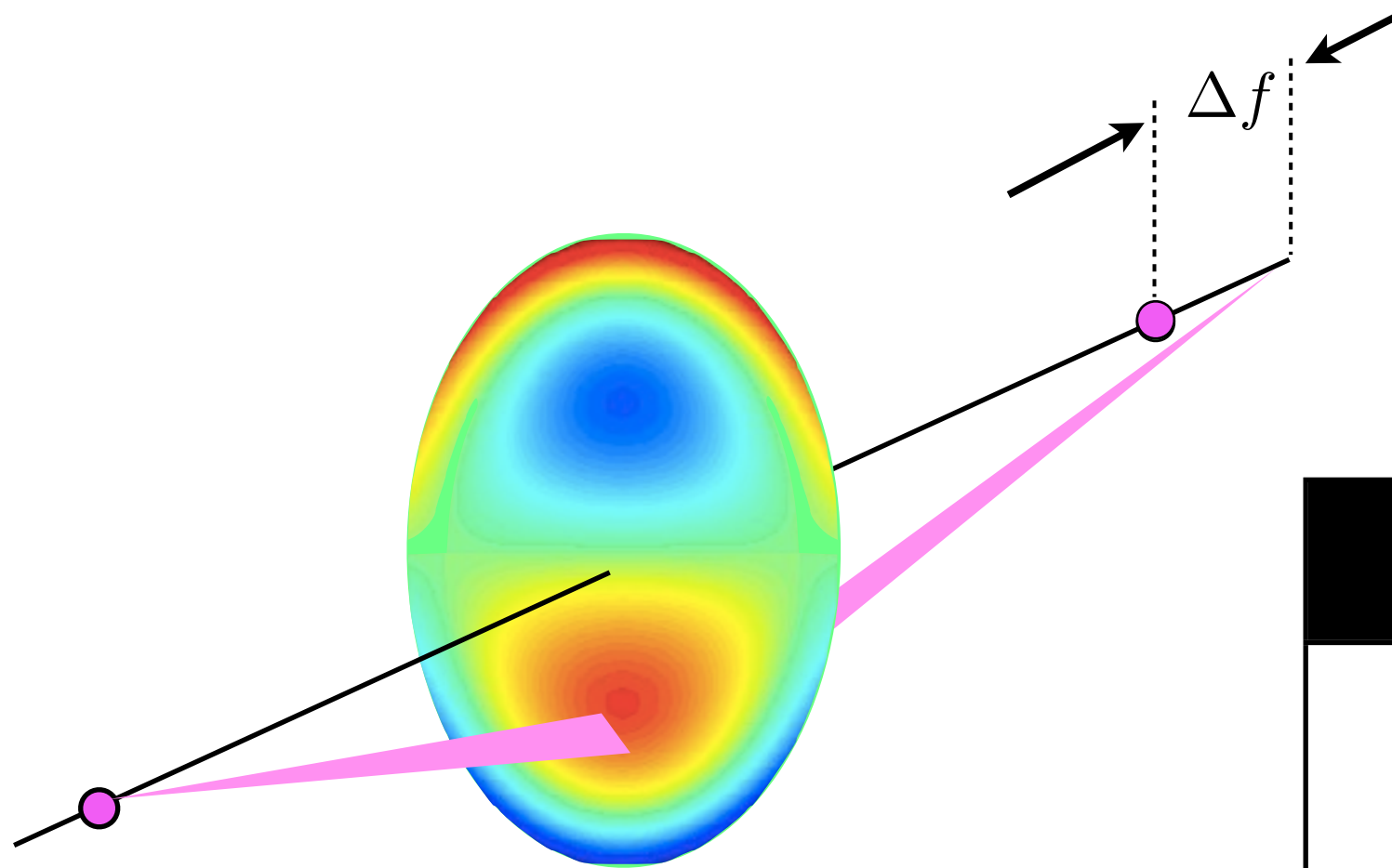
Z6: Coma



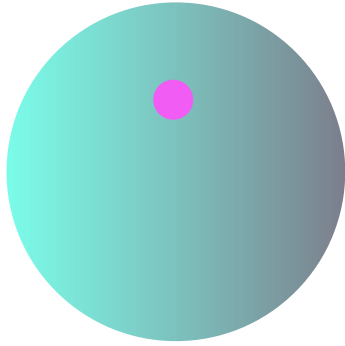

Curvature signature

Probe	Δf
	

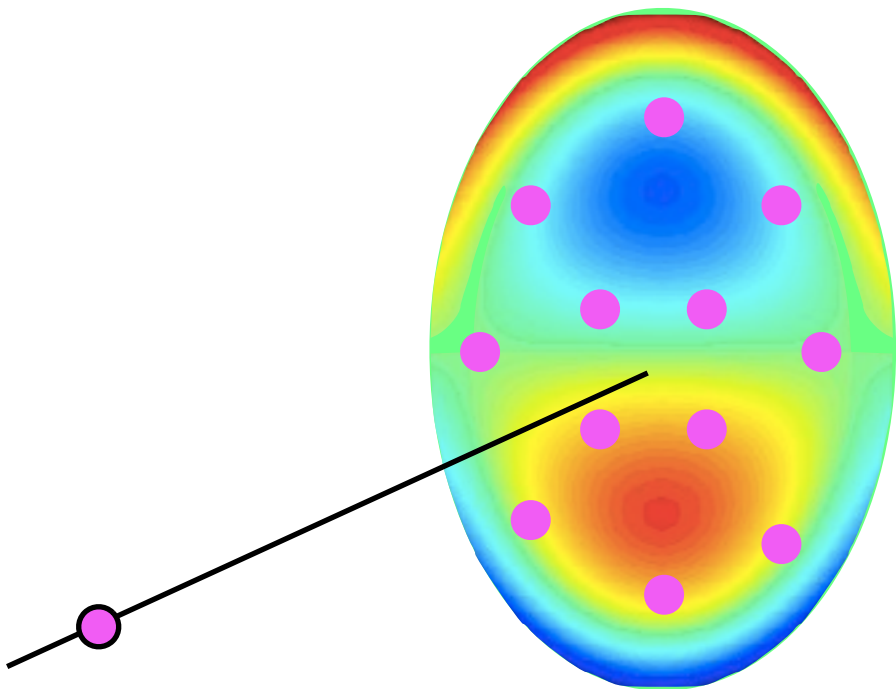
Z6: Coma



Curvature signature

Probe	Δf
	

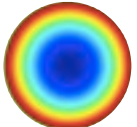
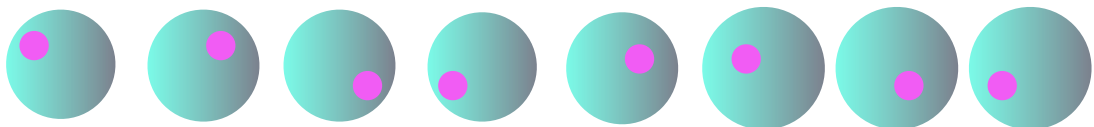
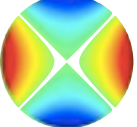
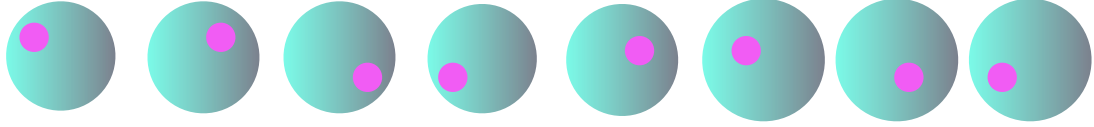
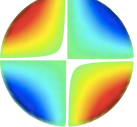

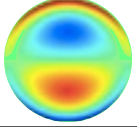

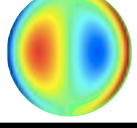

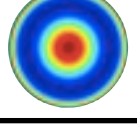

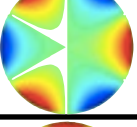

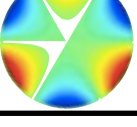

Z6: Coma



Curvature signature

Probe	Δf
	-
	+
	-
	-
	+
	-







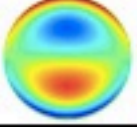

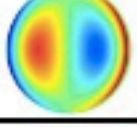

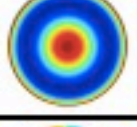

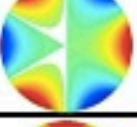

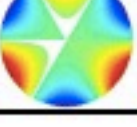

Curvature signatures of Zernike polynomials

N	Aberration	Probe	Δf
3	Focus 		[+,-,+,-,-,+]
4	Stig 		[-,-,+,-,-,+]
5	Stig 		[-,-,+,+,-,+]
6	Coma 		[+,-,+,-,+,+]
7	Coma 		[+,+,+,-,-,+]
8	Spherical 		[-,+,+,+,-,+]
9	Trifoil 		[+,-,-,-,-,+]
10	Trifoil 		[+,-,-,+,+,+]

Store for later use...

Curvature library



N	Aberration	Probe	Δf
3	Focus 		[+, -, +, -, -, +]
4	<u>Stig</u> 		[-, -, +, -, -, +]
5	<u>Stig</u> 		[-, -, +, +, -, +]
6	Coma 		[+, -, +, -, +, +]
7	Coma 		[+, +, +, -, -, +]
8	Spherical 		[-, +, +, +, -, +]
9	<u>Trifoil</u> 		[+, -, -, -, -, +]
10	<u>Trifoil</u> 		[+, -, -, +, +, +]

Store for later use...

Curvature library

Wavefront

Focus shifts

$$\left[\text{SEMATECH USB Drive} \right] \cdot \left[\text{Wavefront} \right] = \left[\Delta f \right]$$

Curvature library

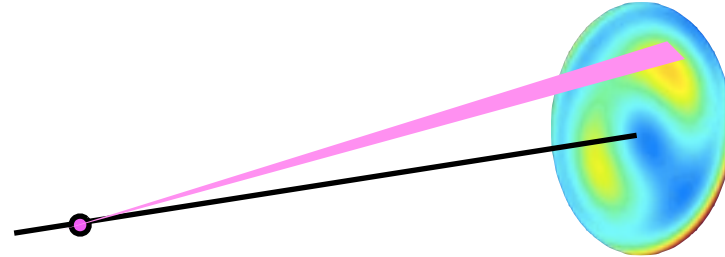
Focus shifts

Wavefront

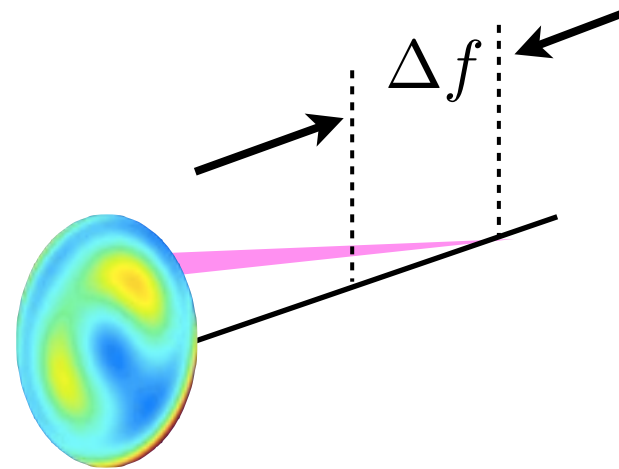
$$\left[\text{SEMATECH USB Drive} \right] \cdot \left[\Delta f \right] \approx \left[\text{Wavefront} \right]$$

Wavefront sensor outline

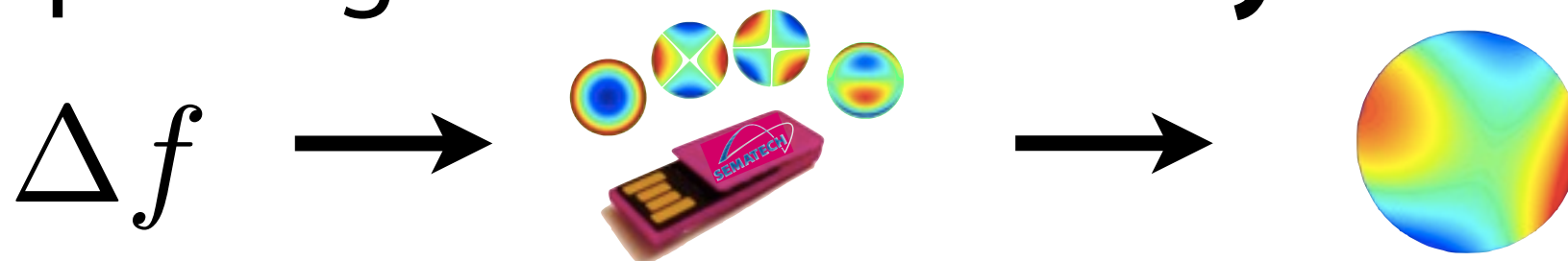
Step 1: Probe localized regions of the pupil



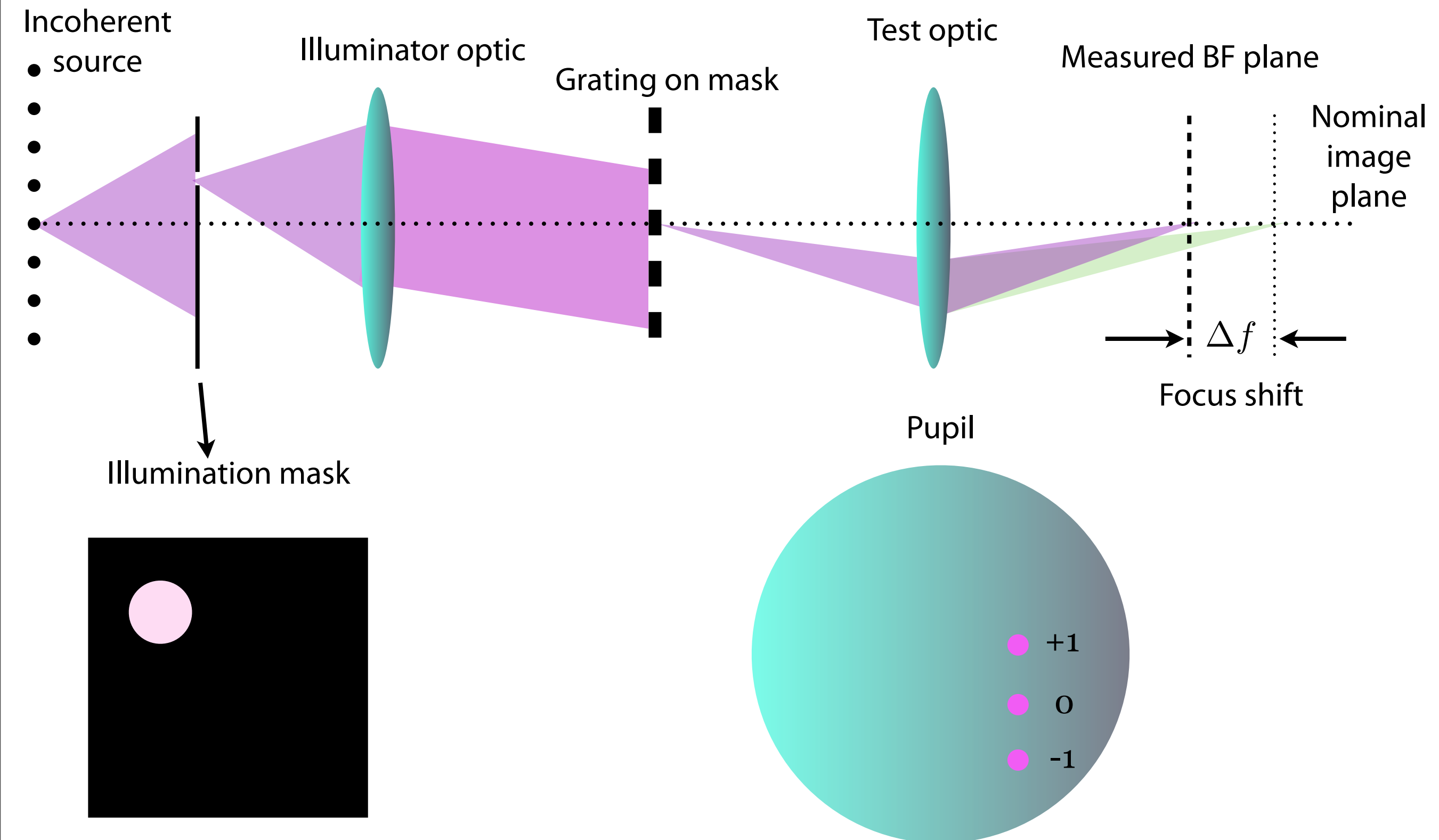
Step 2: Find the plane of **best focus** for each probe location



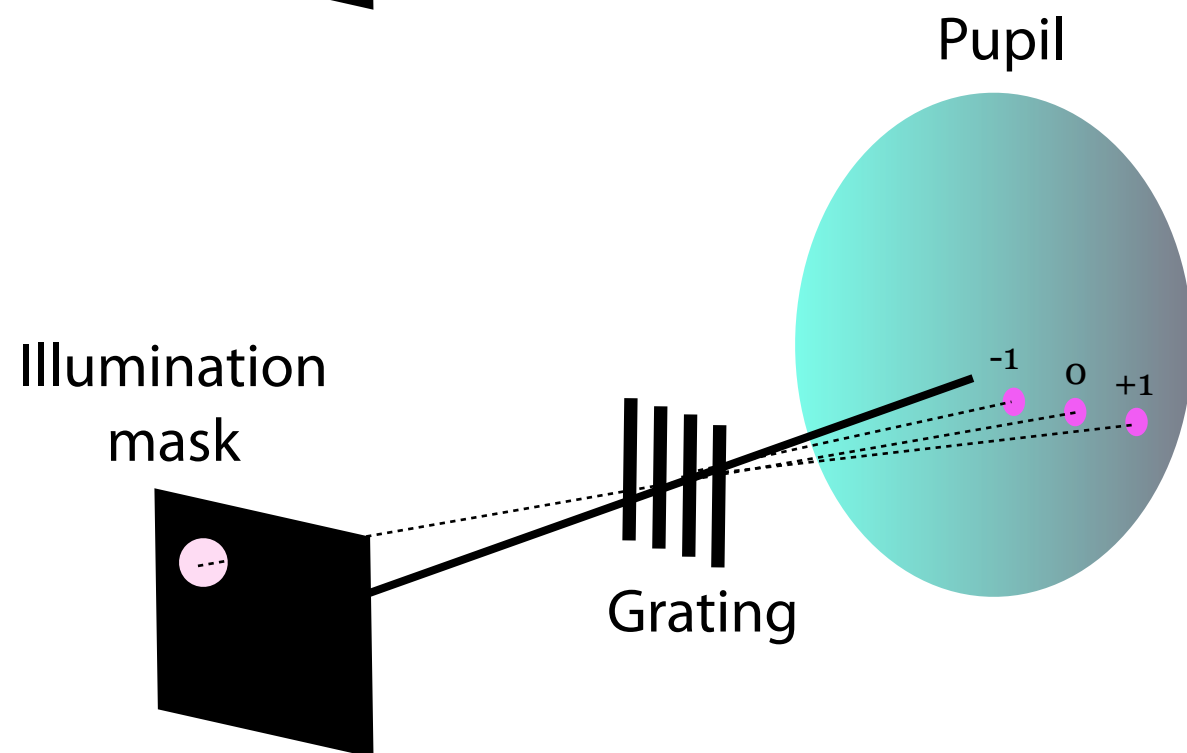
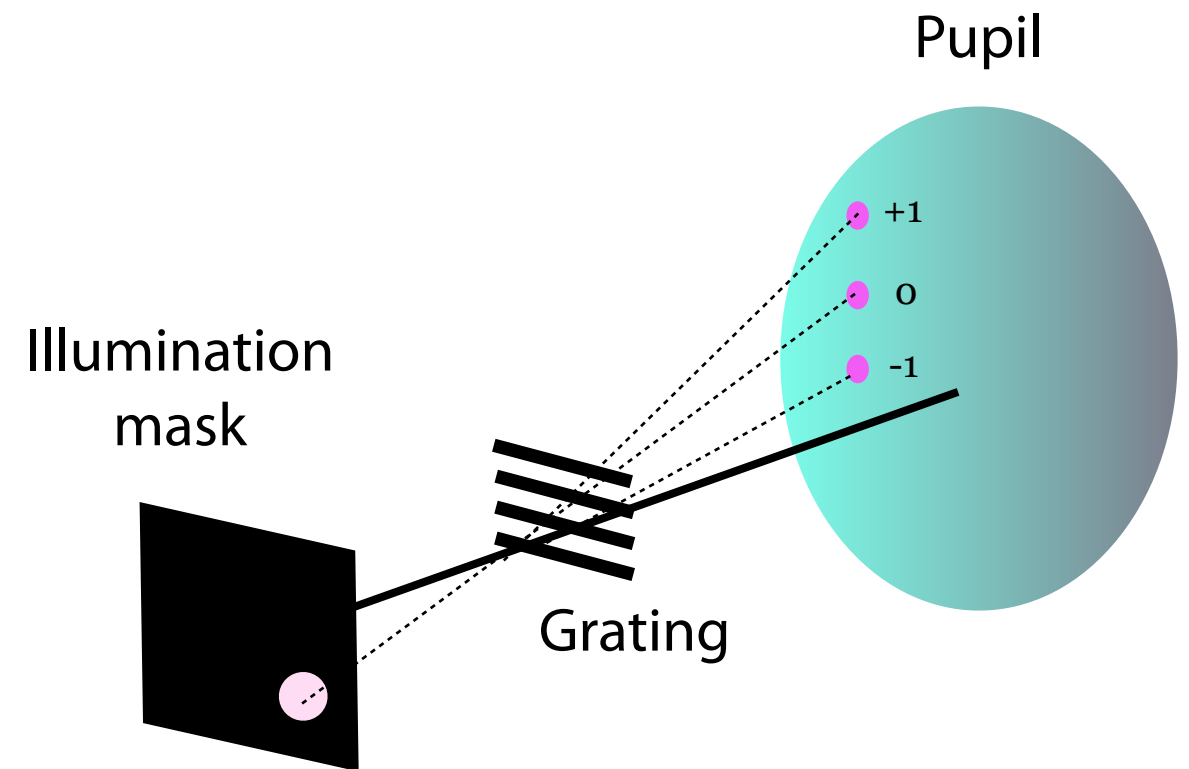
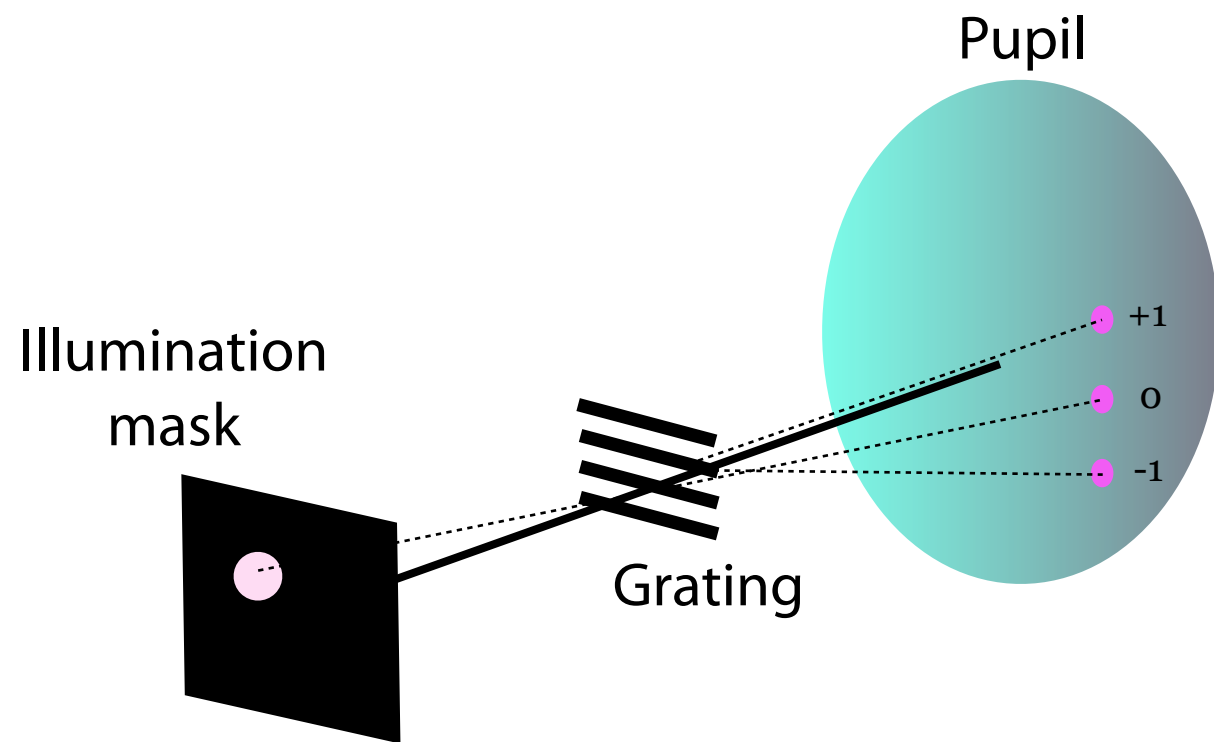
Step 3: Convert these focus shifts into an aberration map using **curvature library**



Schematic of illumination principle



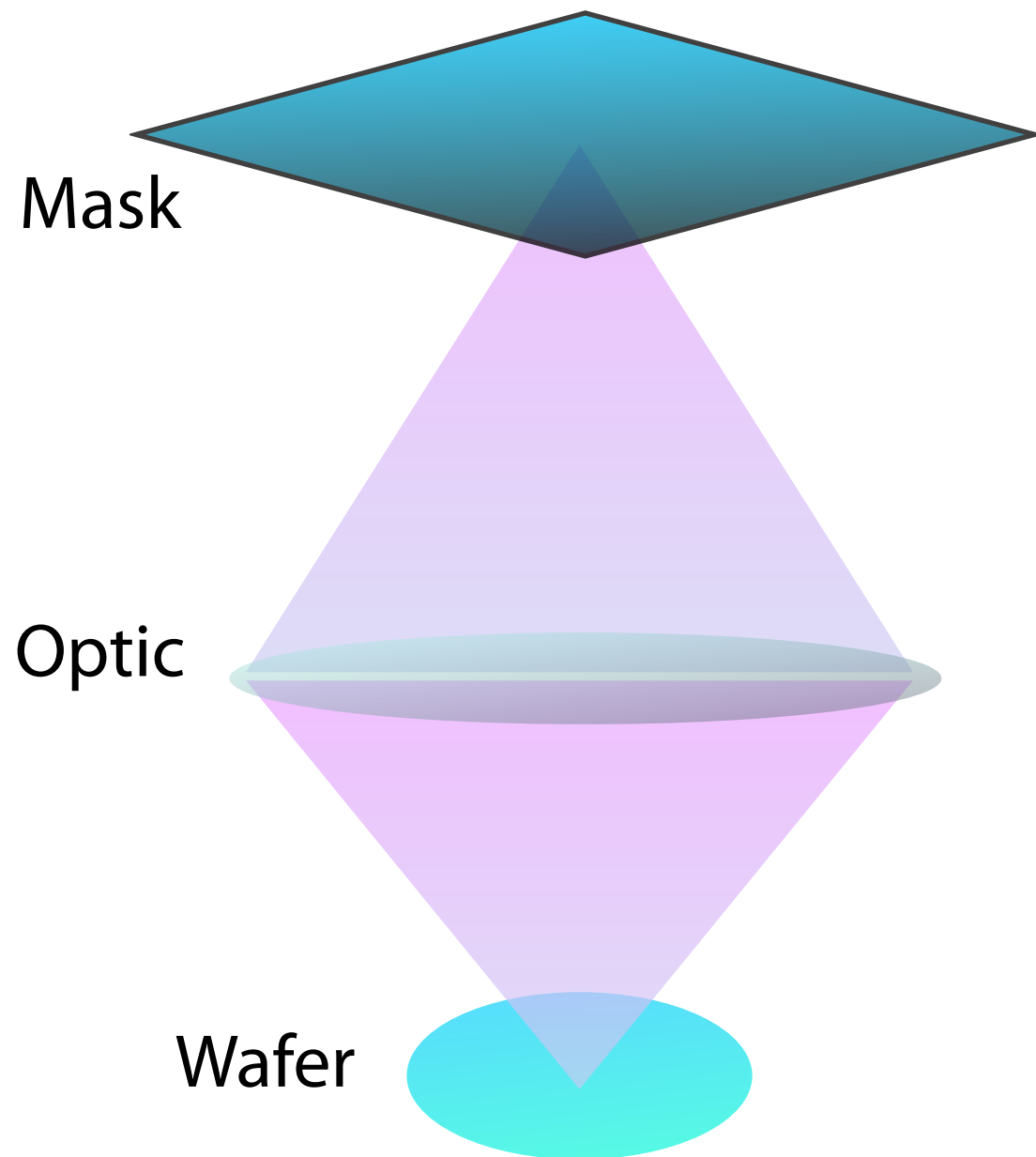
Customized illumination to probe pupil



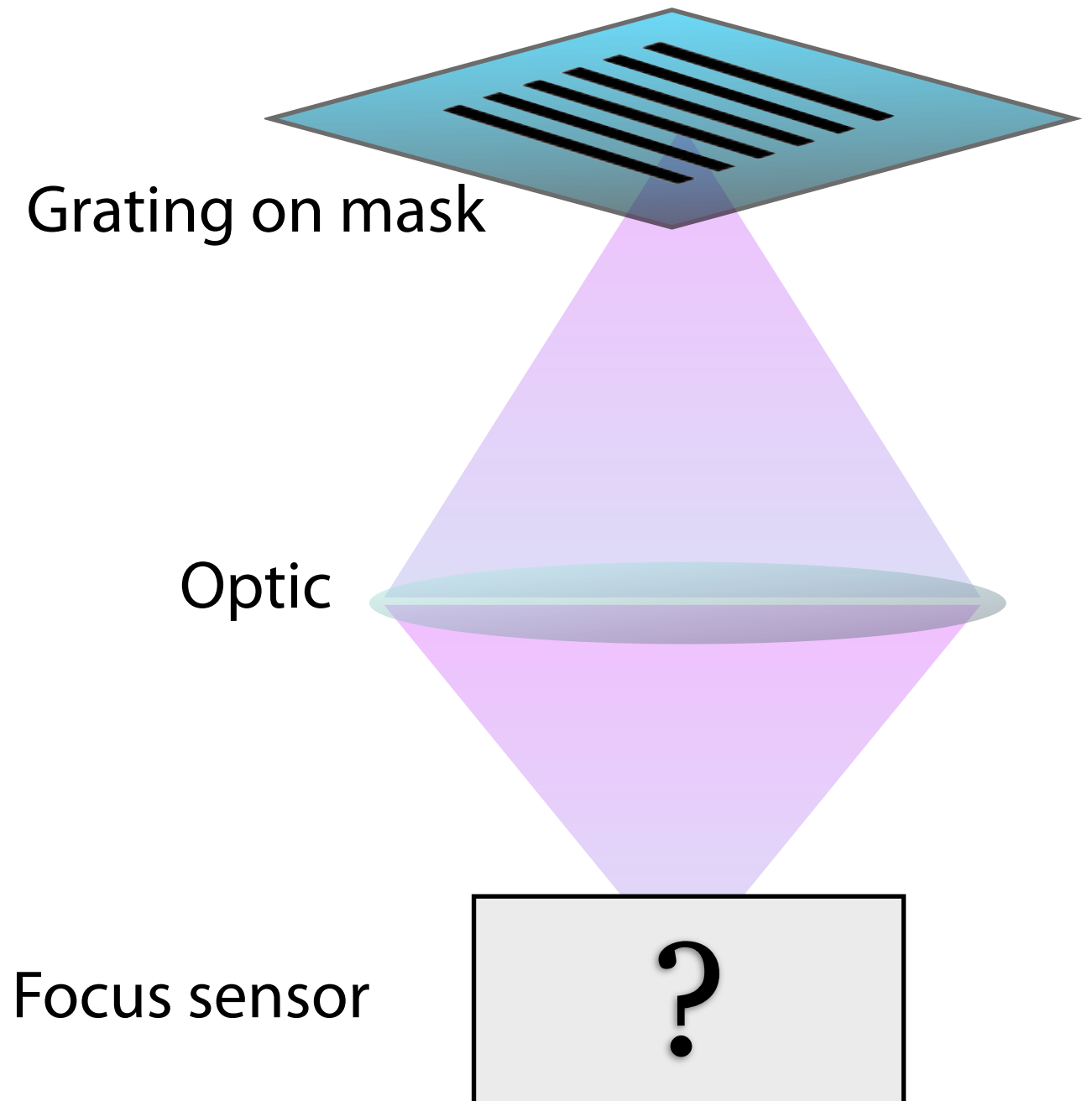
- Order separation determined by grating pitch
- Probe orientation determined by grating orientation
- Zero order location determined by illumination mask

Swap wafer with focus sensor

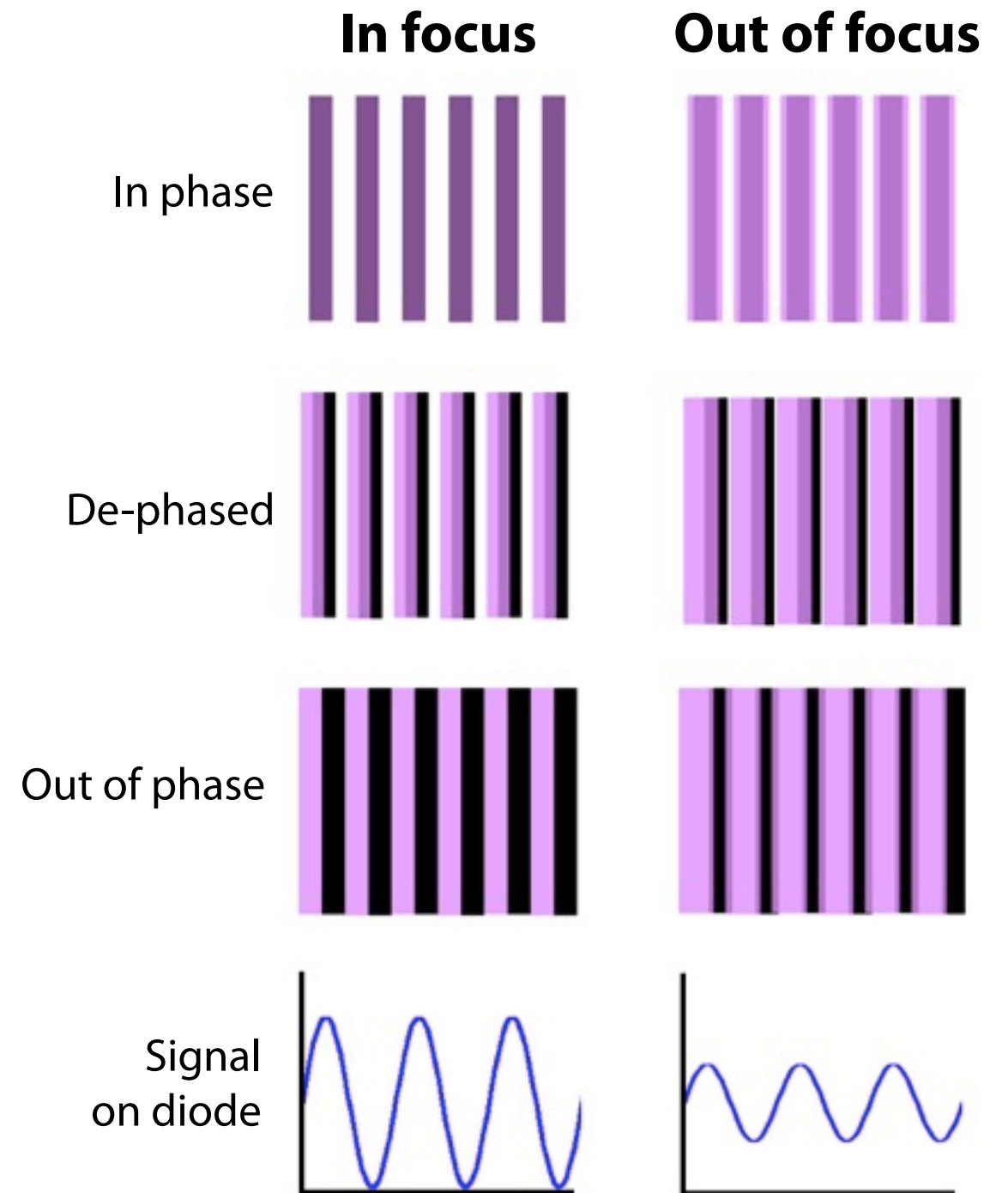
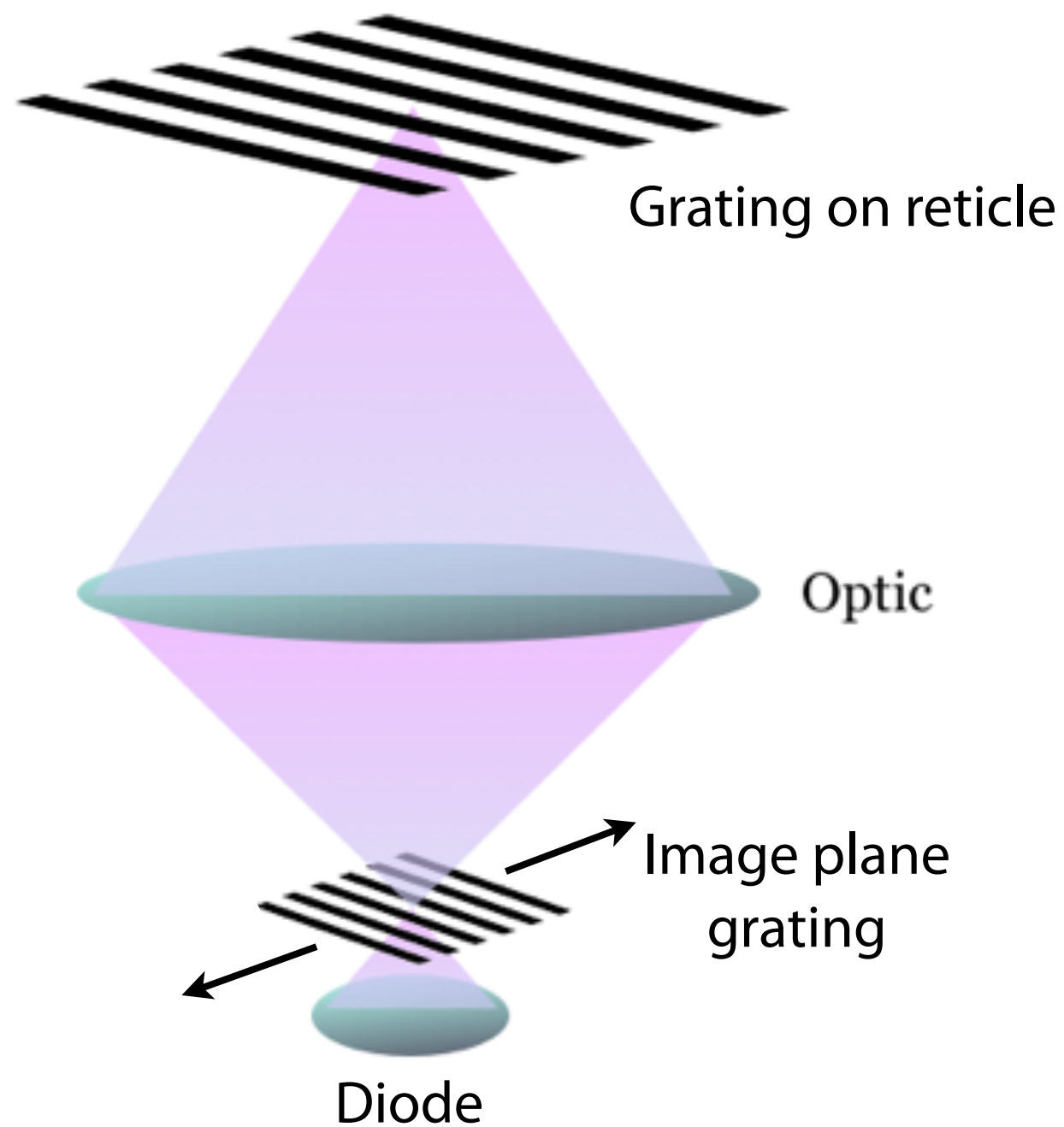
Imaging setup



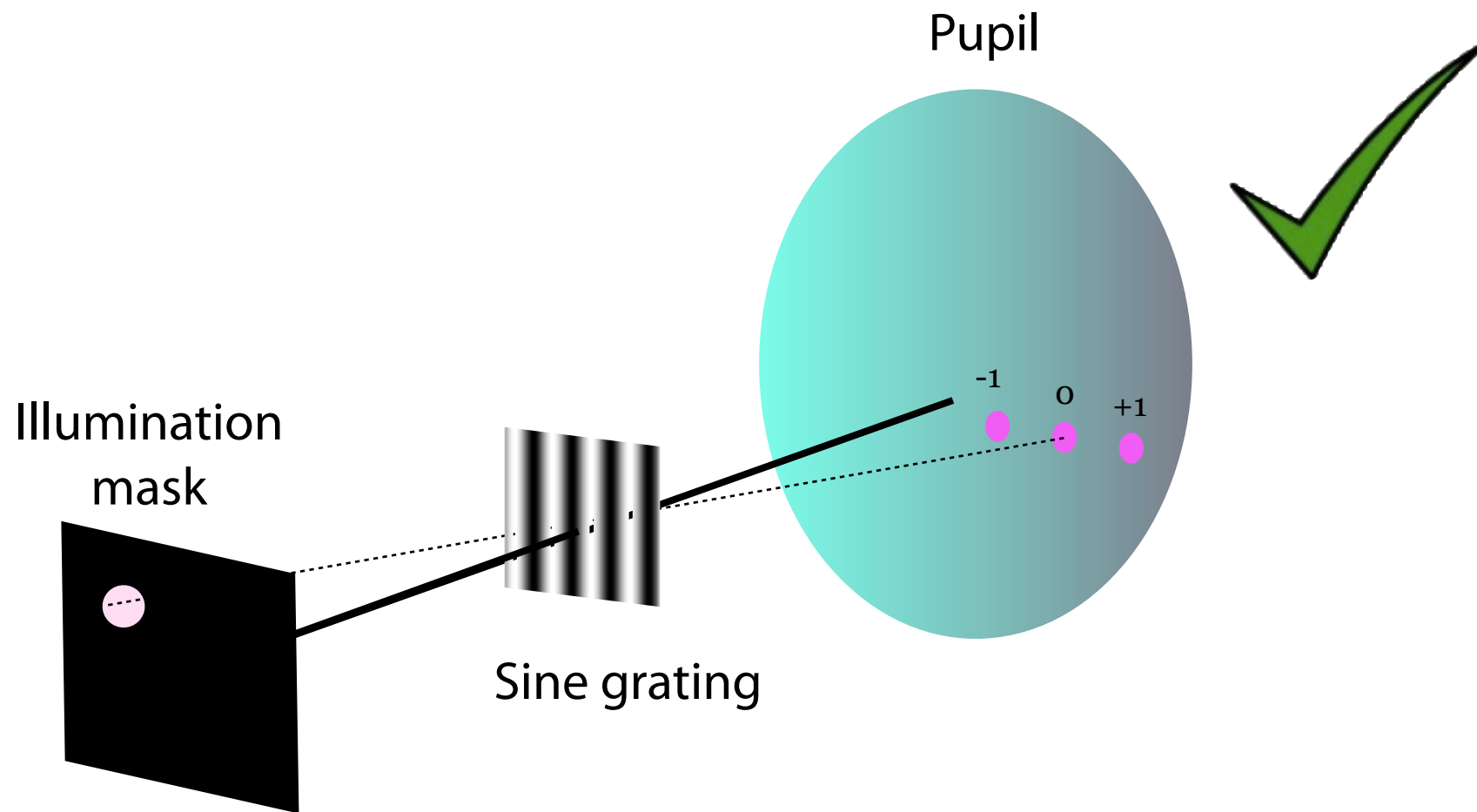
Wavefront sensing setup



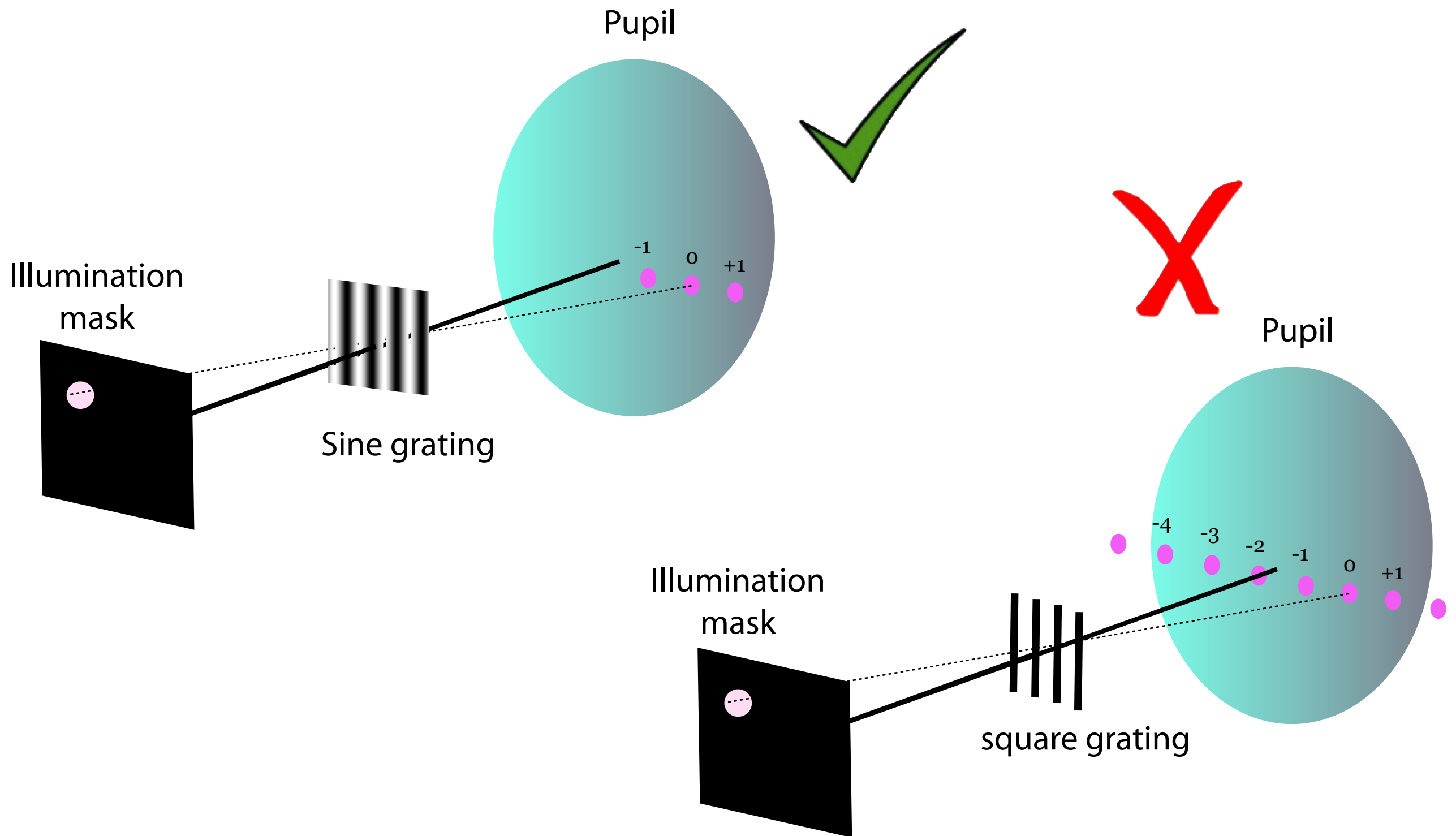
How to measure plane of best focus?



Binary gratings have many orders

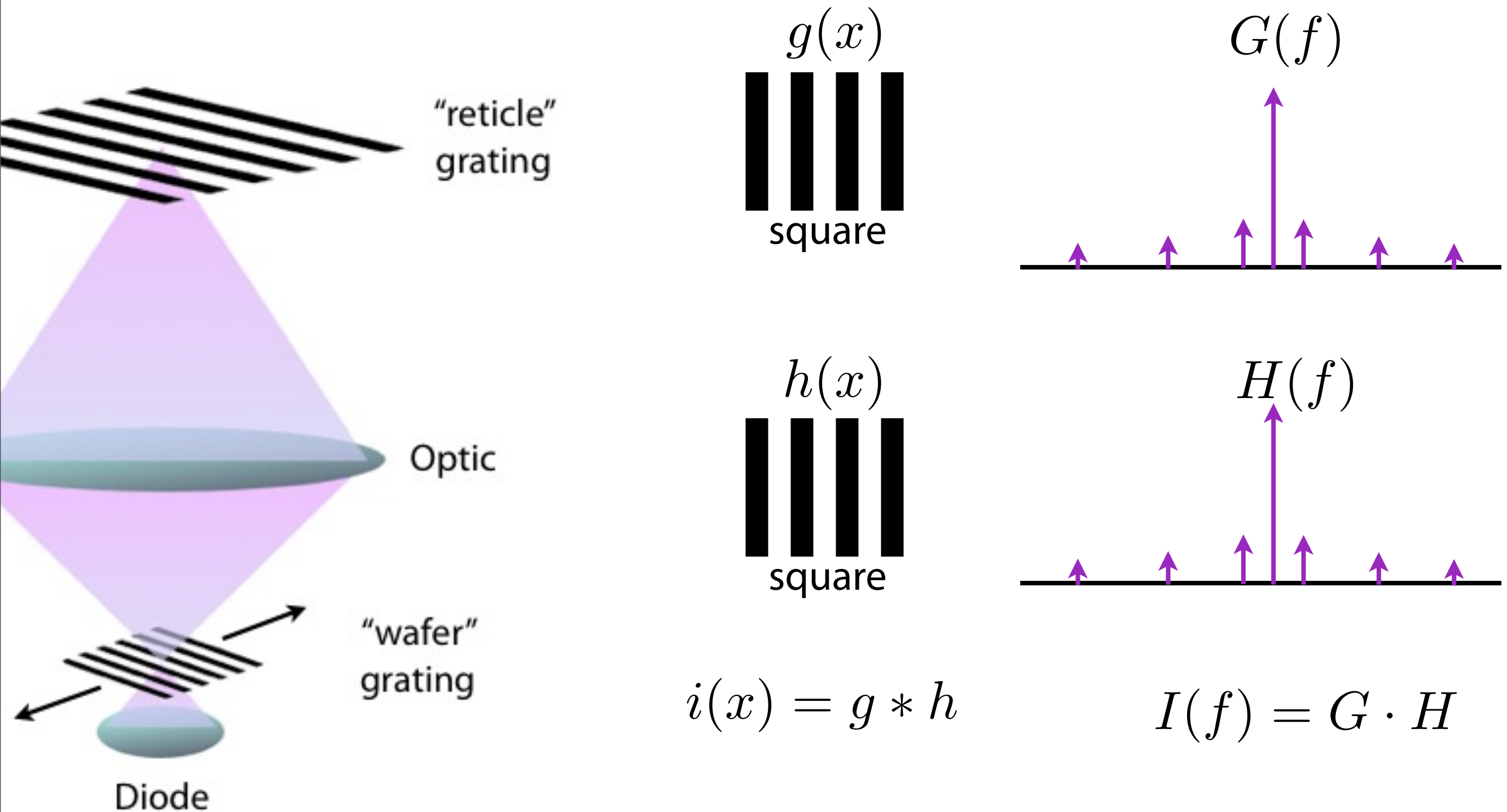


Binary gratings have many orders

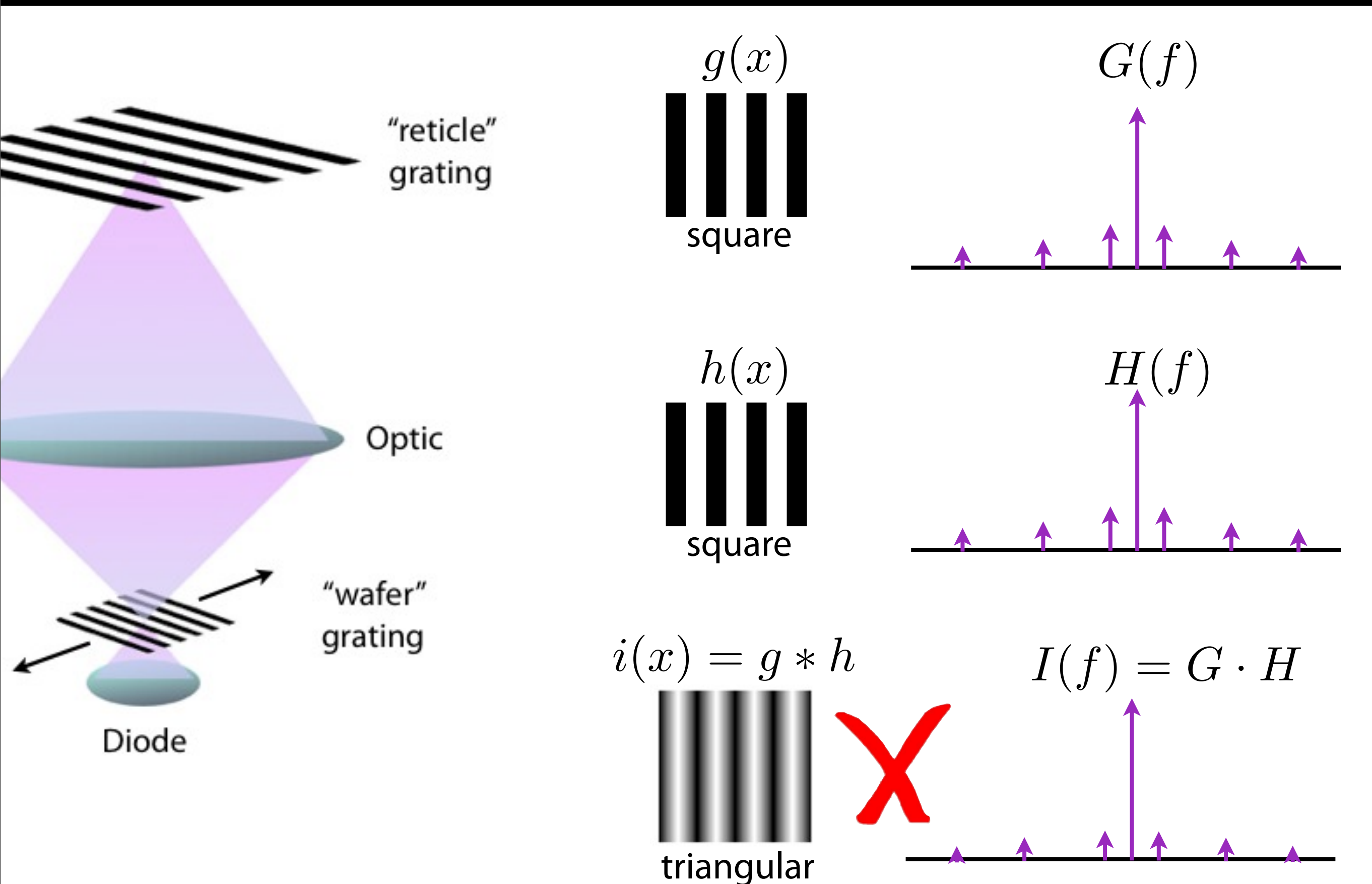


Question: *Can we use a binary structure that mimics the properties of a sine grating?*

A trick in the Fourier domain...



A trick in the Fourier domain...

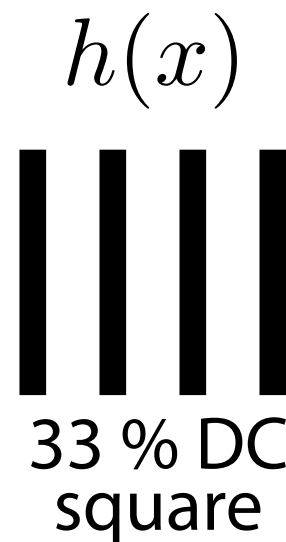


A trick in the Fourier domain...

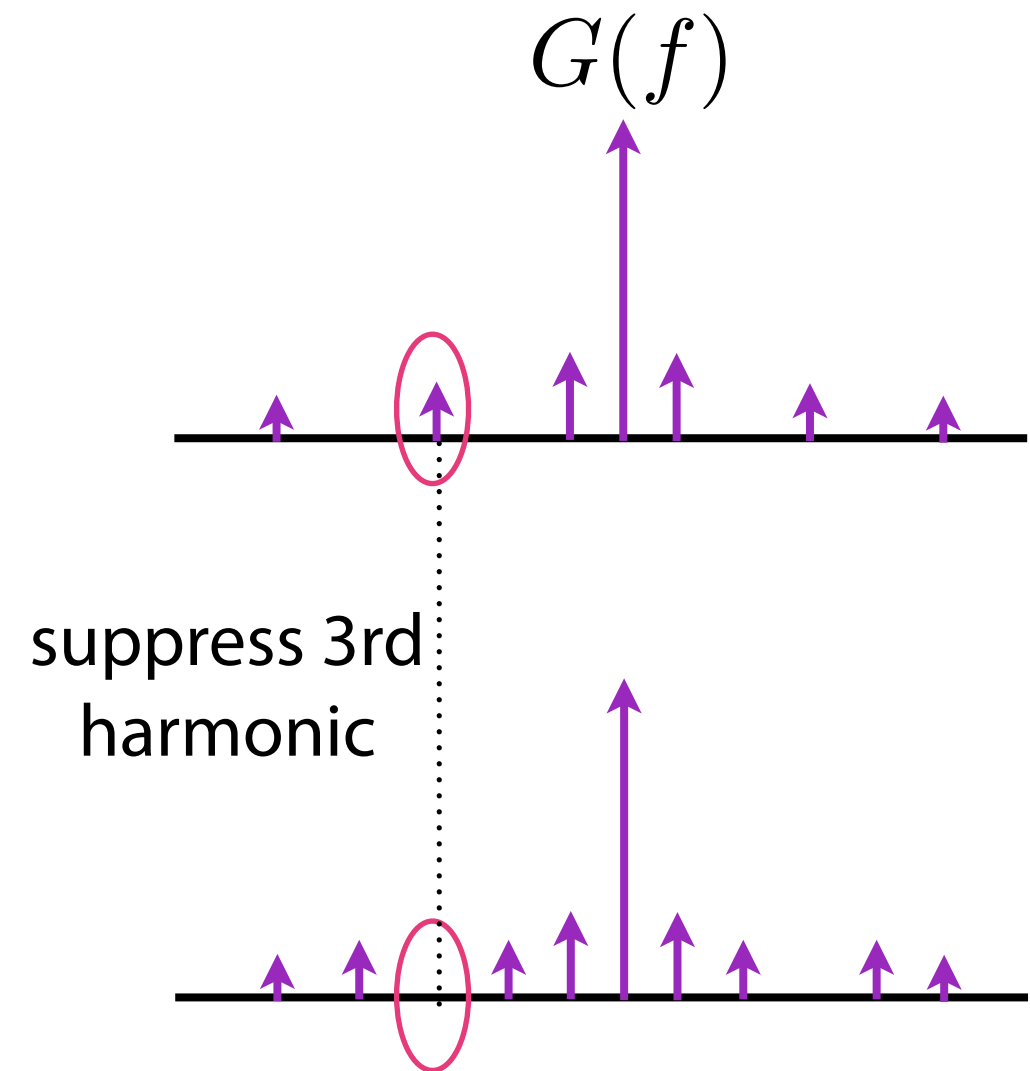
Reticle grating



Wafer grating



$$i(x) = g * h$$



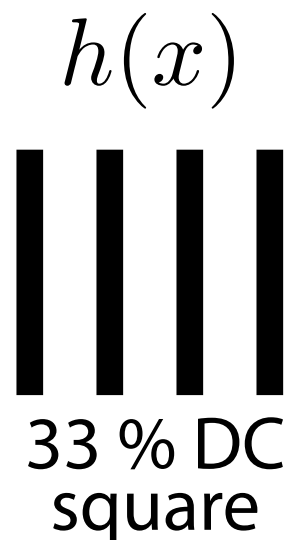
$$I(f) = G \cdot H$$

A trick in the Fourier domain...

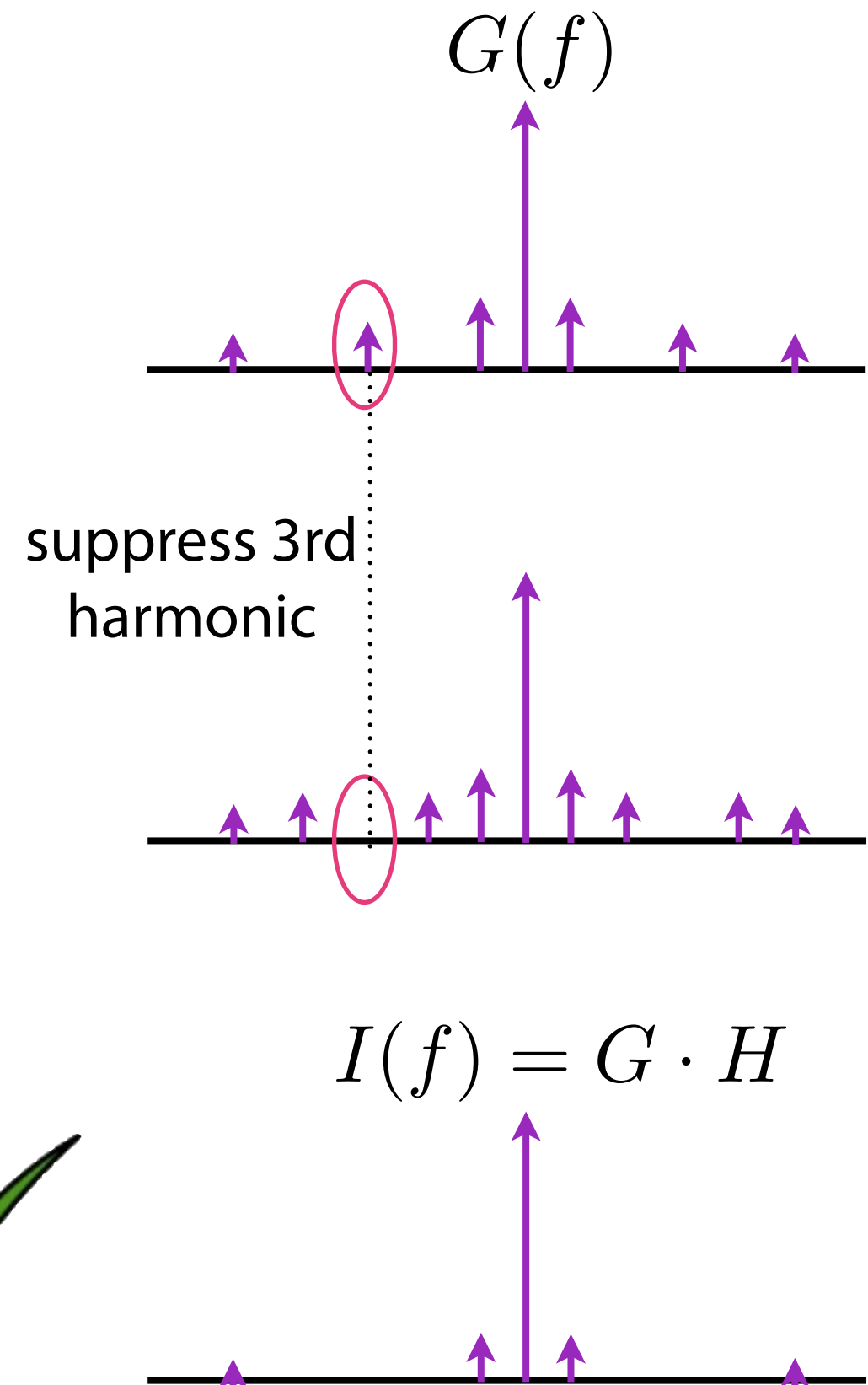
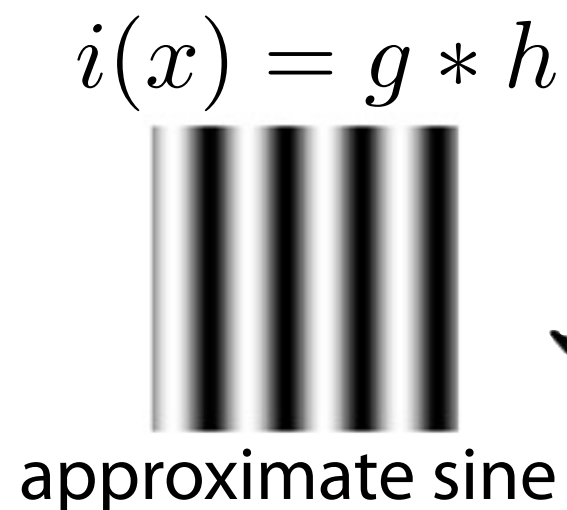
Reticle grating



Wafer grating

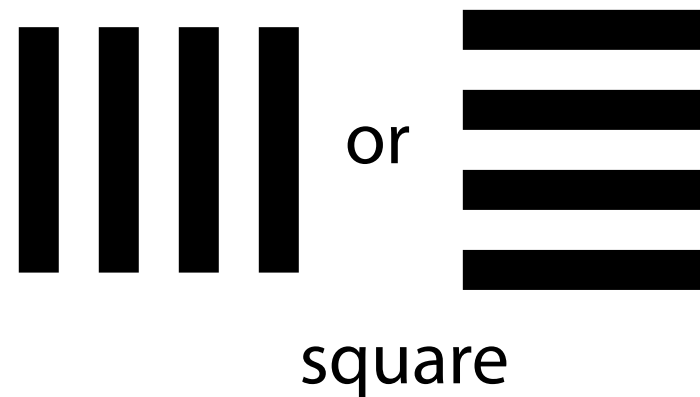


Signal at diode

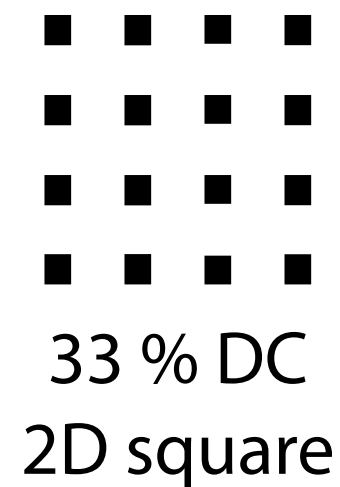


A trick in the Fourier domain...

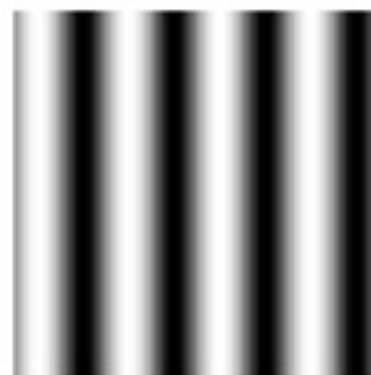
Reticle grating



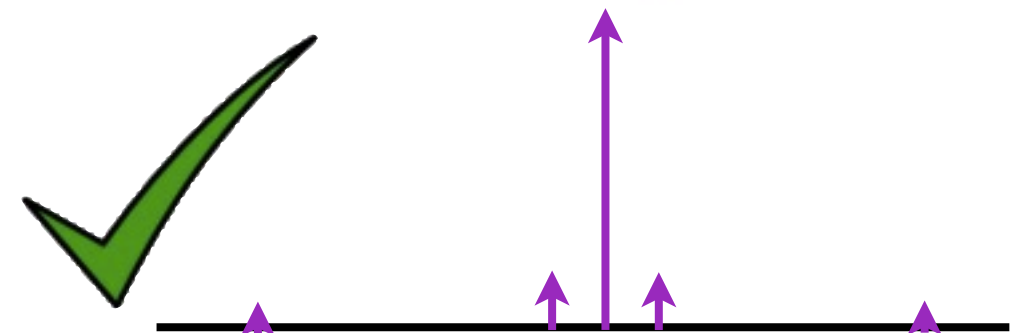
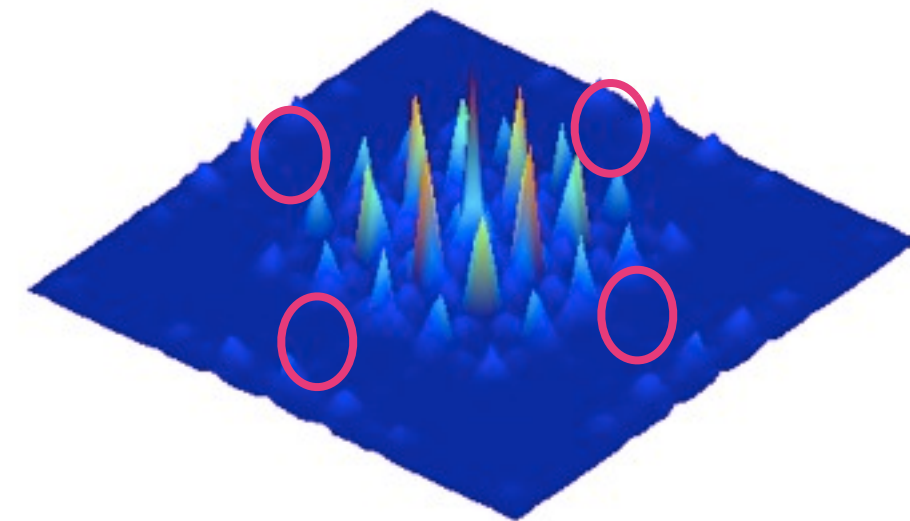
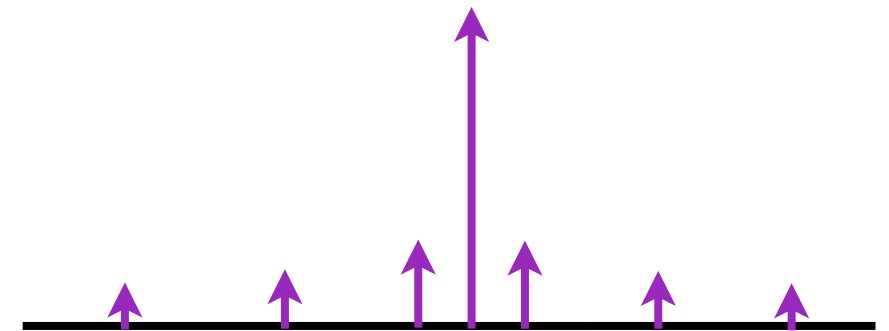
Wafer grating



Signal at diode

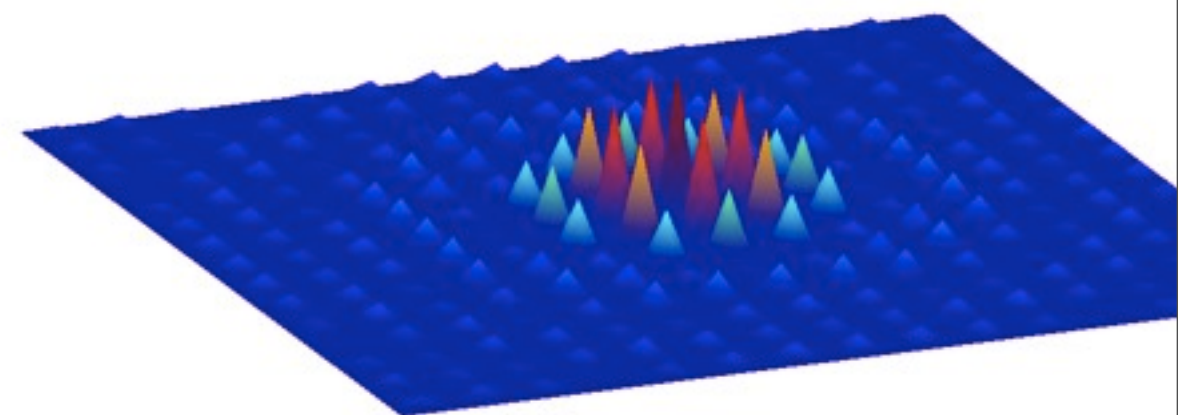
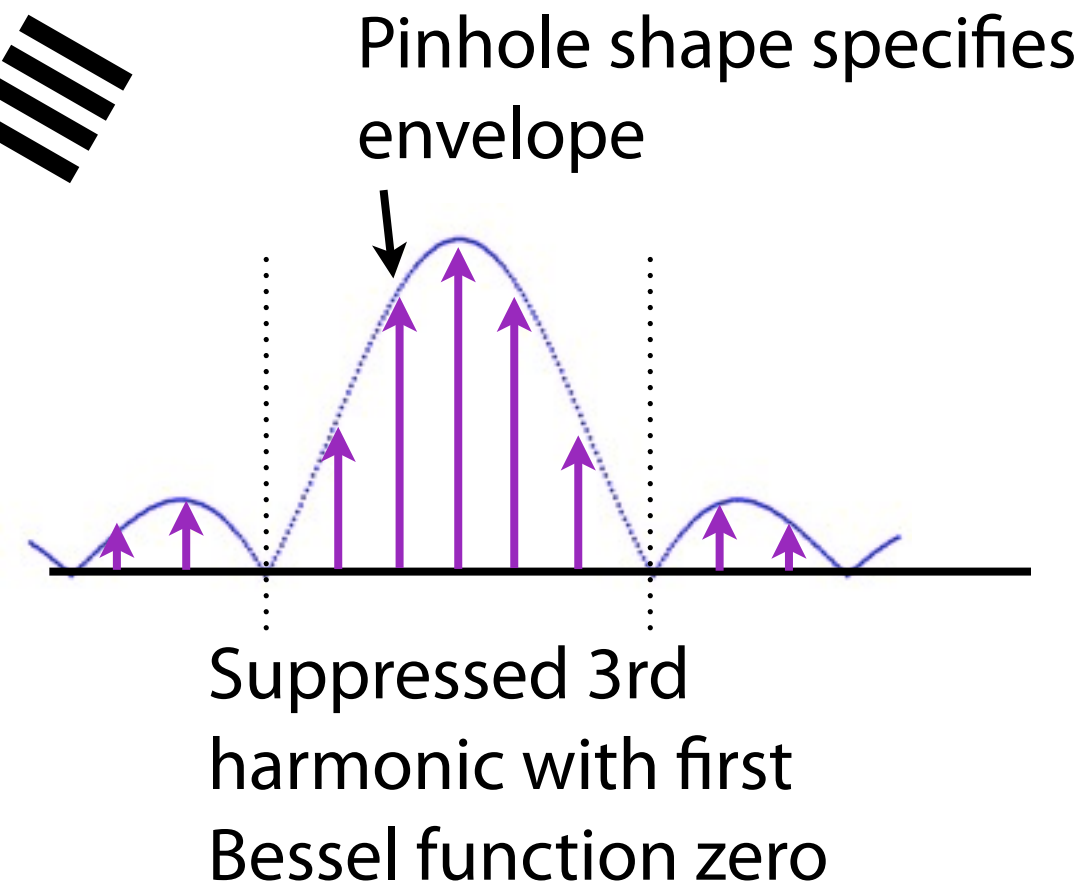
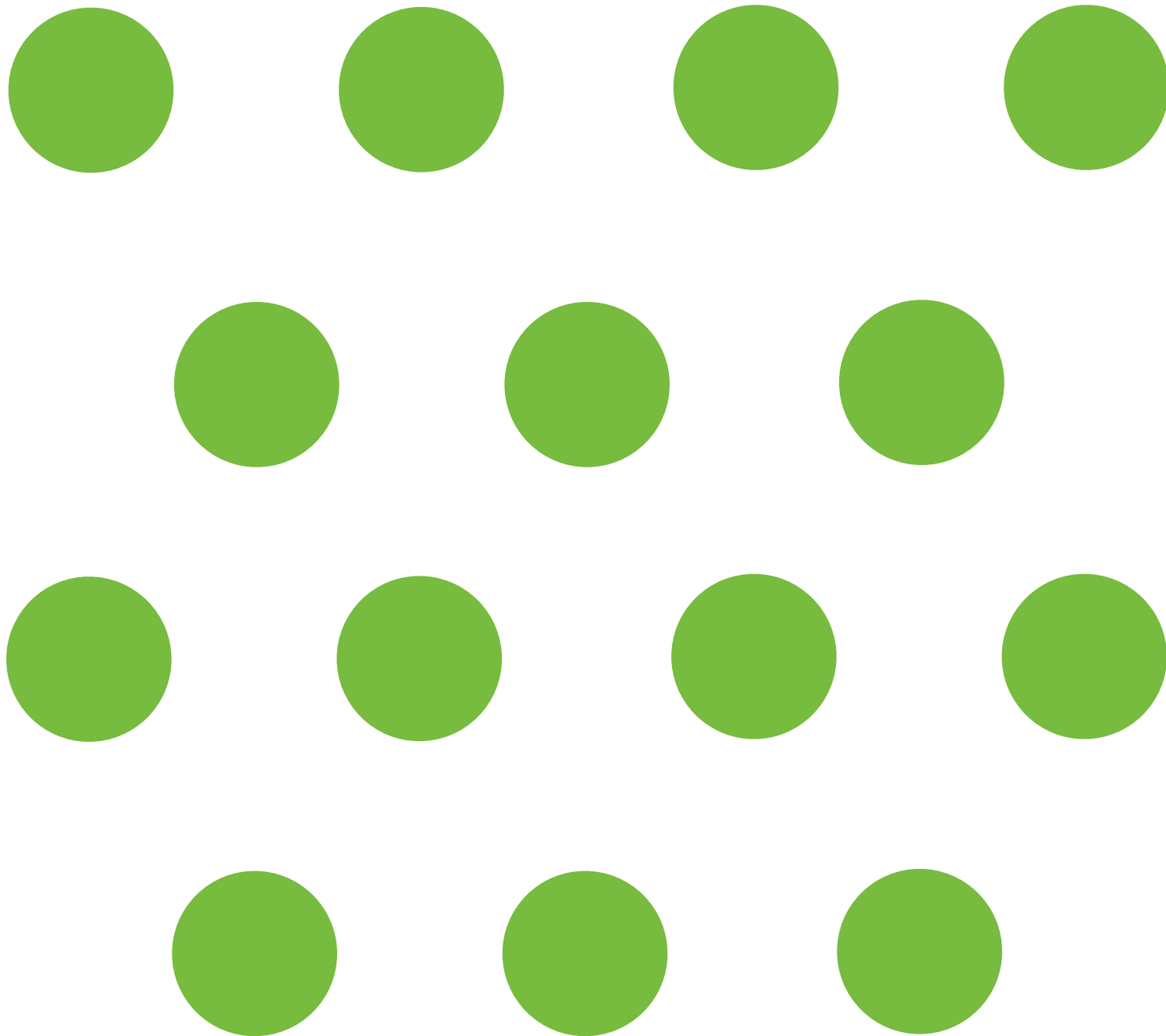


Approximate sine



Pinhole arrays (6-fold symmetry)

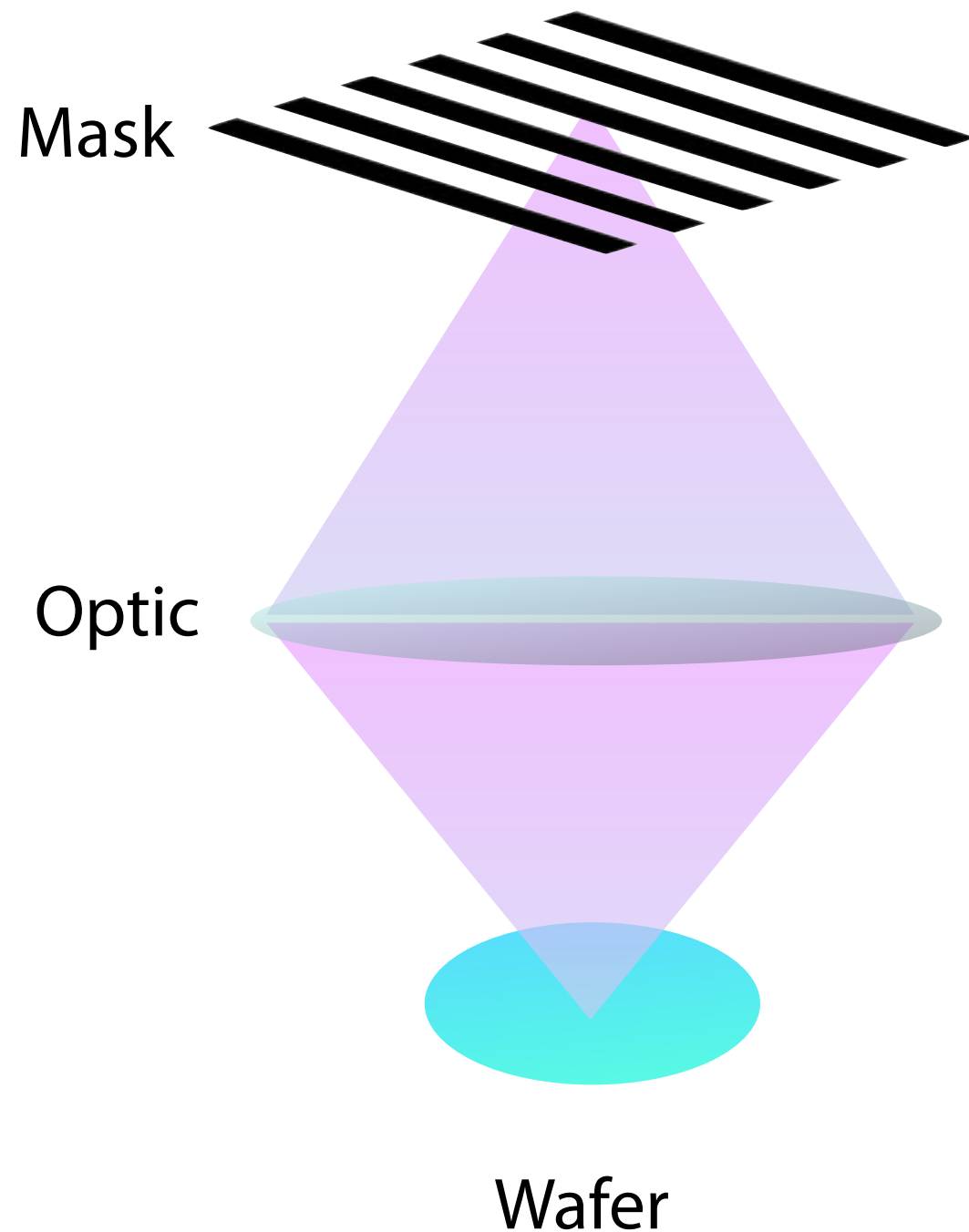
Supports 3 grating orientations: 



$$\frac{\text{CD}}{\text{pitch}} = 0.404$$

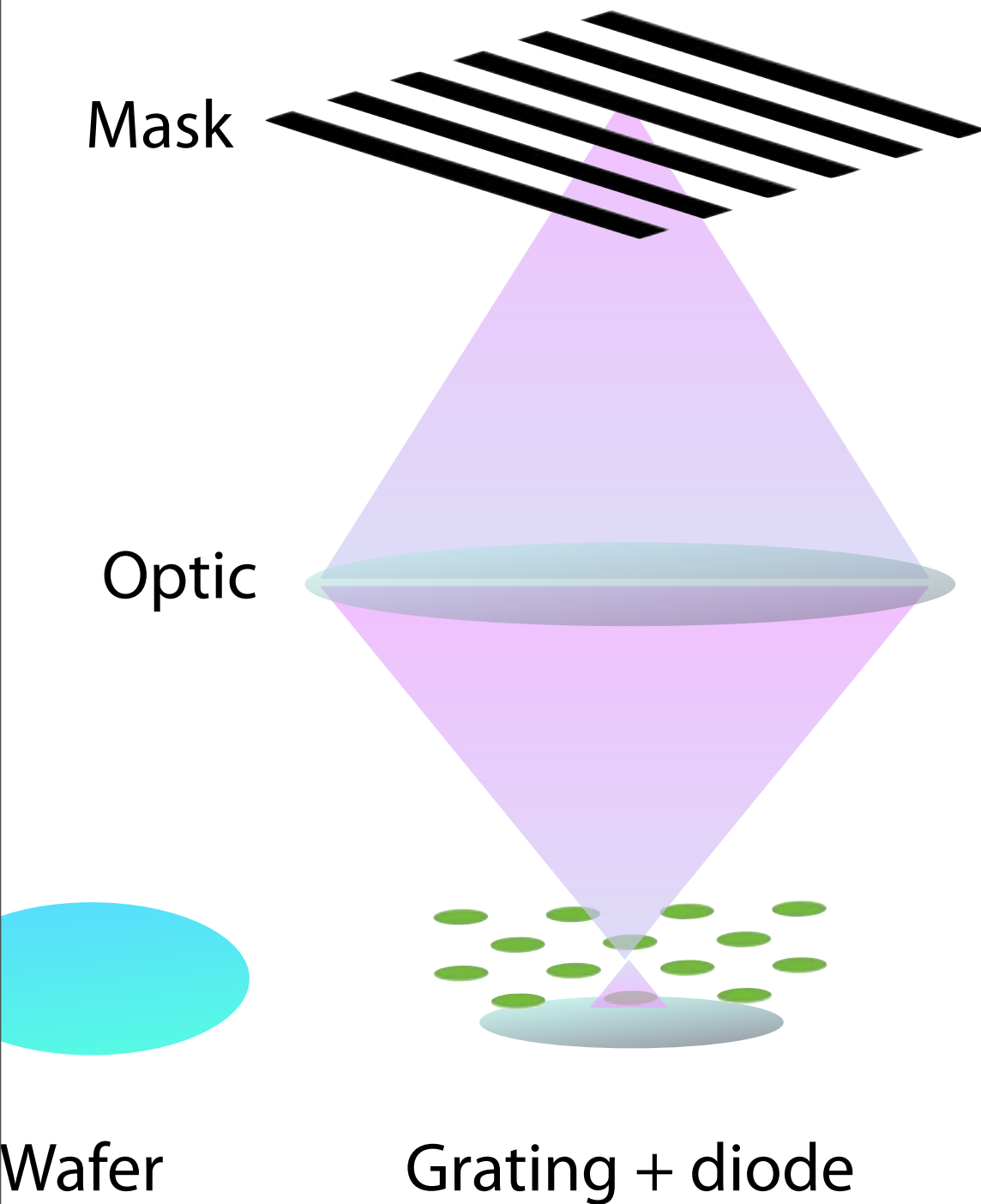
Wafer and focus sensor are easily swapped

Imaging setup



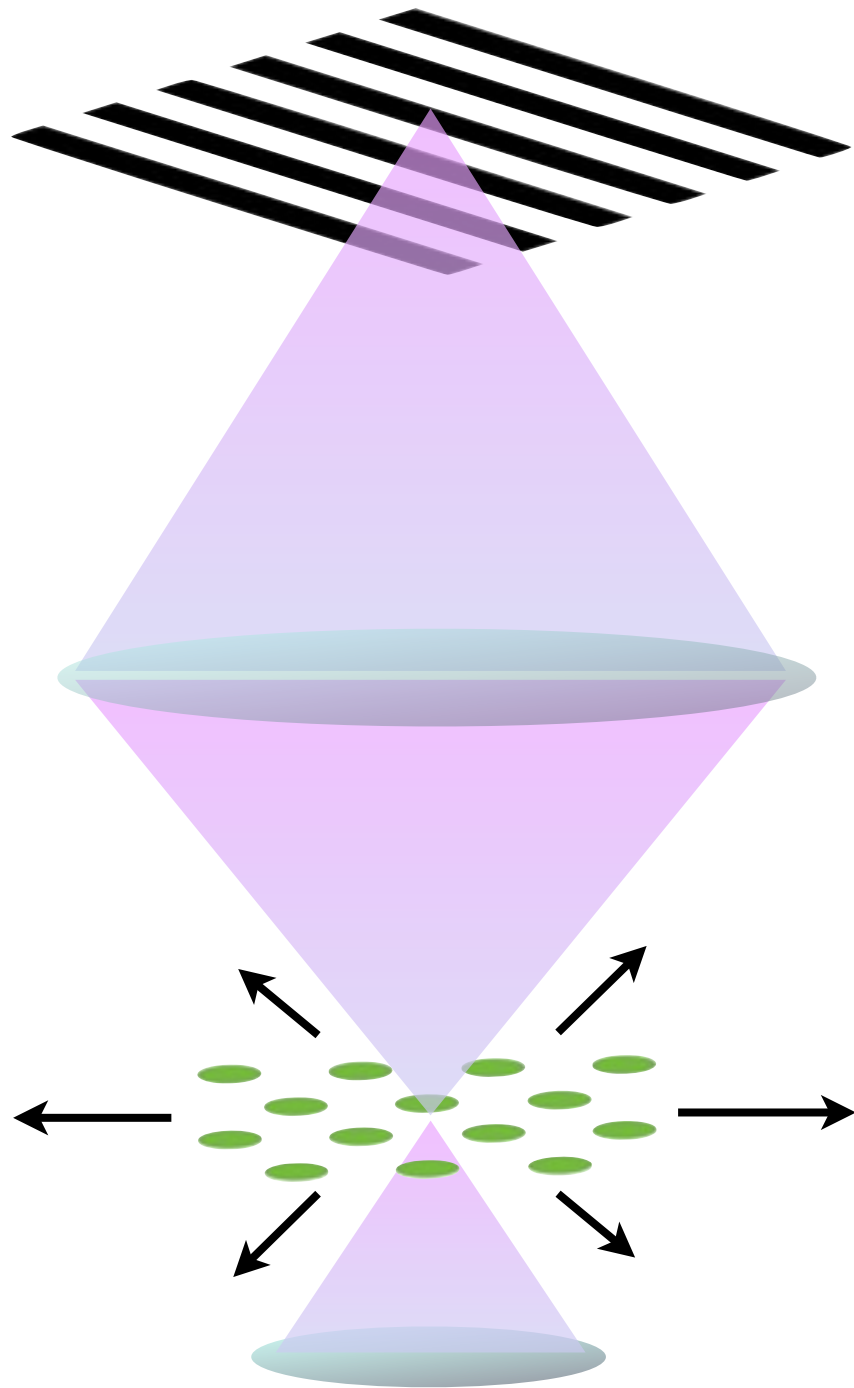
Simple yet versatile technique

Imaging setup



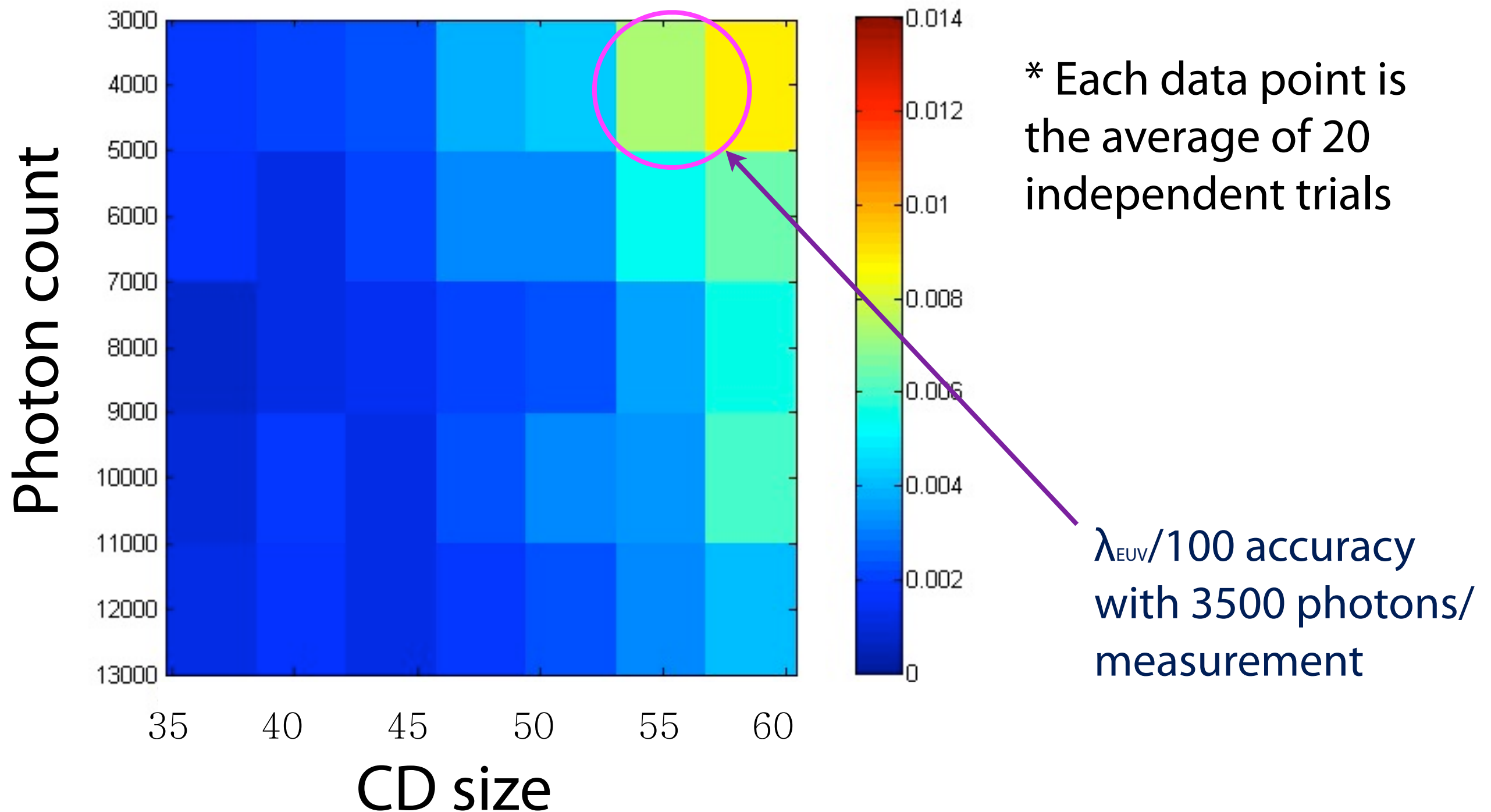
Wafer

Grating + diode



- Use randomly selected wavefront from Zernike polynomials 1-24
- 16 pupil probe points, 3 grating orientations
- 21 steps through focus
- Various values of grating pitch and shot noise were considered

Wavefront reconstruction error

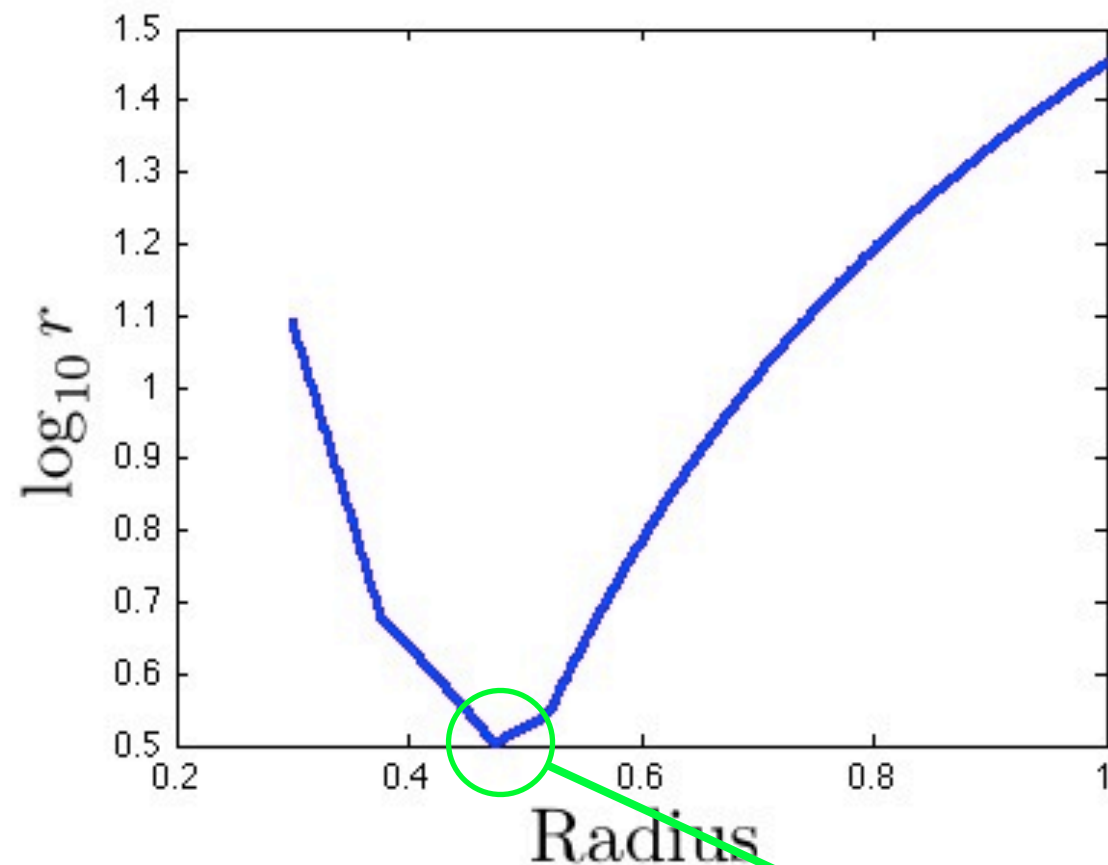
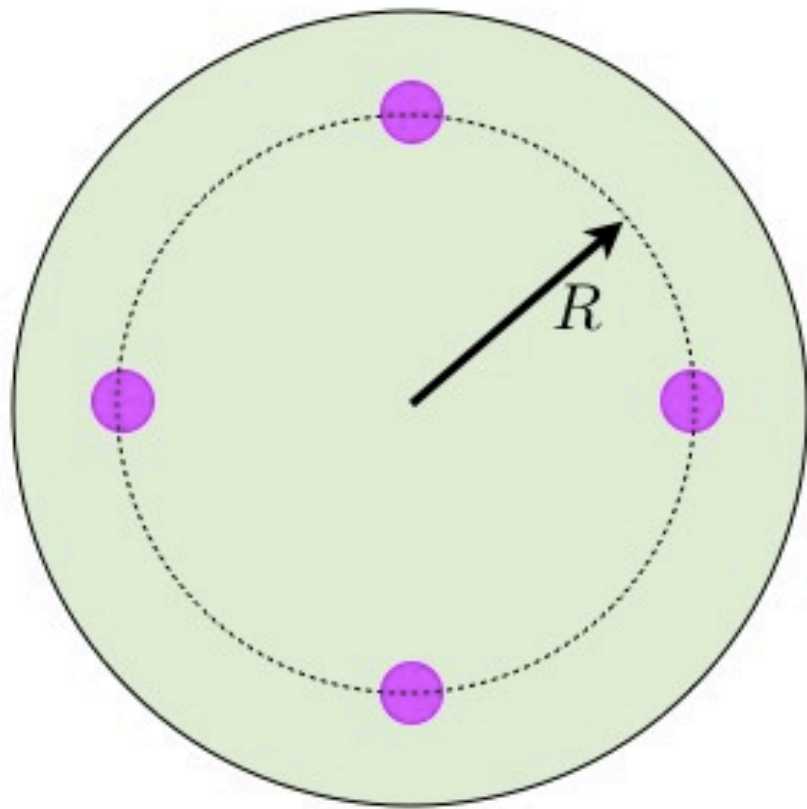


Optimizing probe configuration

Optimizing probe configuration

The condition number can be used as a metric for optimizing probe configuration

4 probe points:

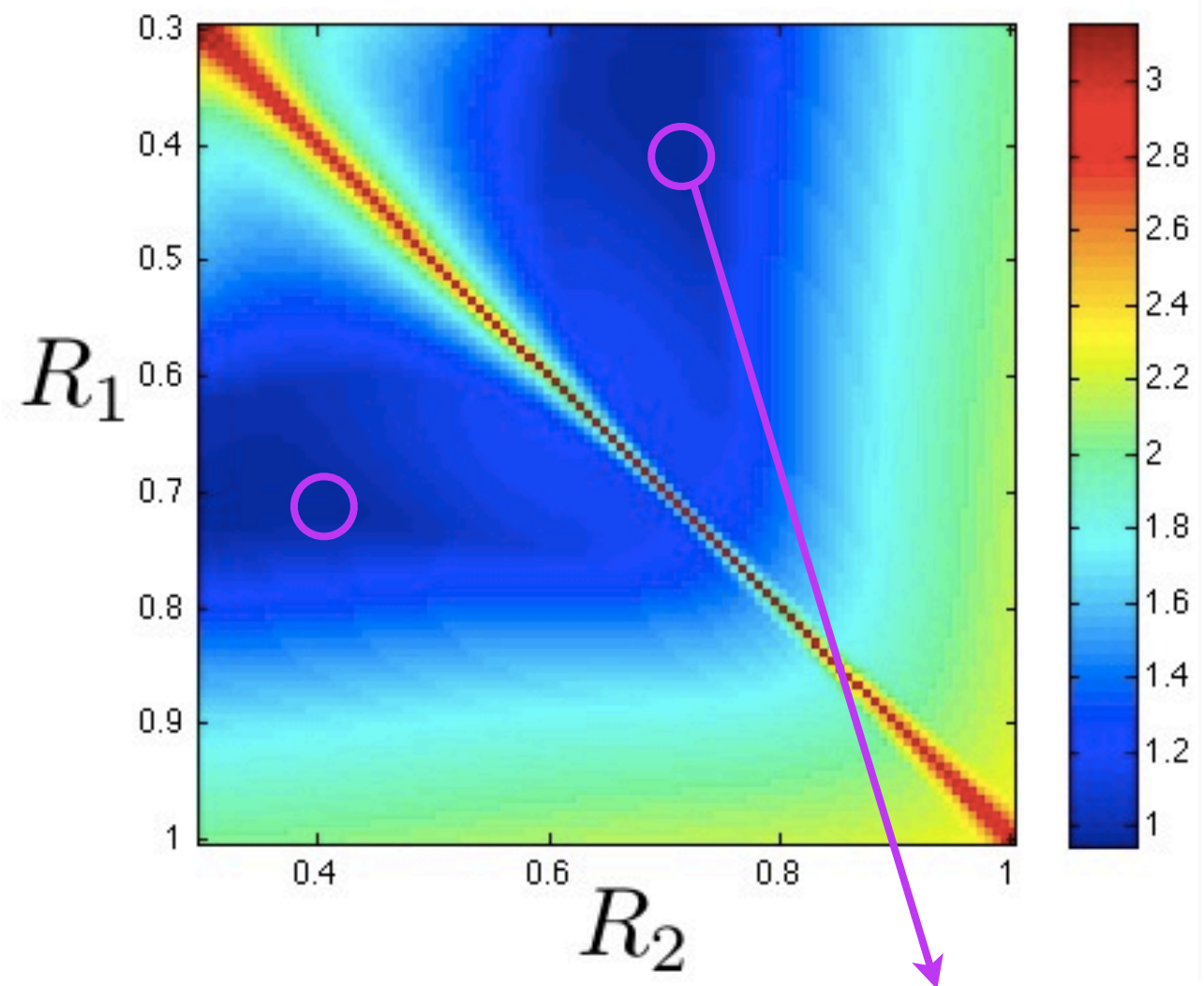
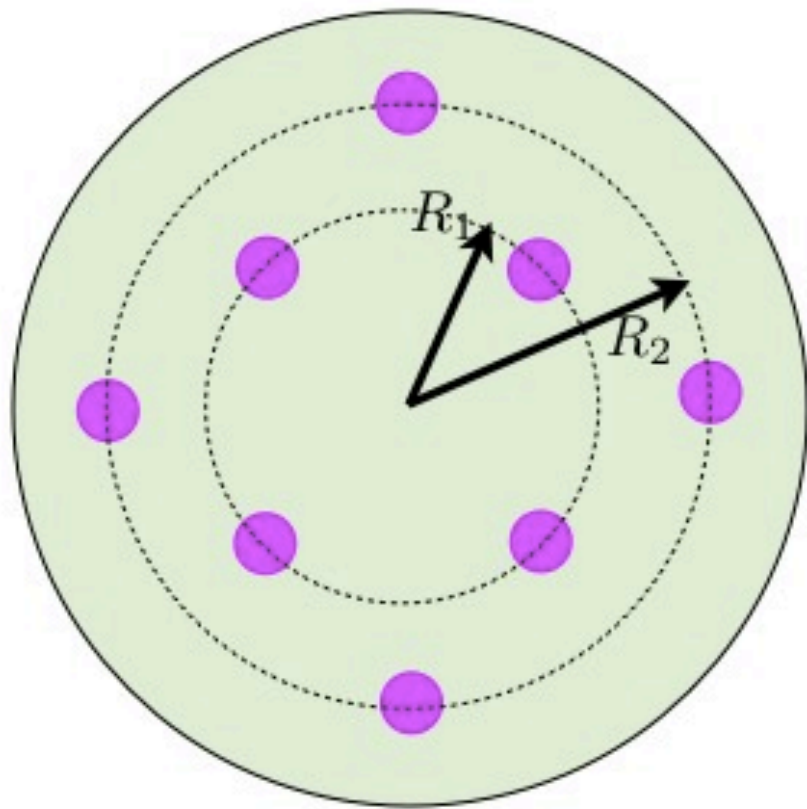


$$R = 0.47$$

Optimizing probe configuration

The condition number can be used as a metric for optimizing probe configuration

8 probe points:



$$[R_1, R_2] = [0.41, 0.71]$$

- We have proposed a method for testing the aberrations in an optical system by measuring localized curvature variations
- Curvature is calculated by measuring the focus shifts in specific locations across the pupil
- The focus sensor working principle is based on a grating-on-grating contrast monitor, where the combination of gratings must suppress higher harmonics.
- Numerical simulations have shown accuracy below $\lambda_{\text{EUV}}/100$.
- Strategies are developed for optimizing probe locations for numerical stability

Acknowledgements



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Contact

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